

10 Tera-bits-per-square-inch arrays of self-organized, single crystalline 1D nanomagnets

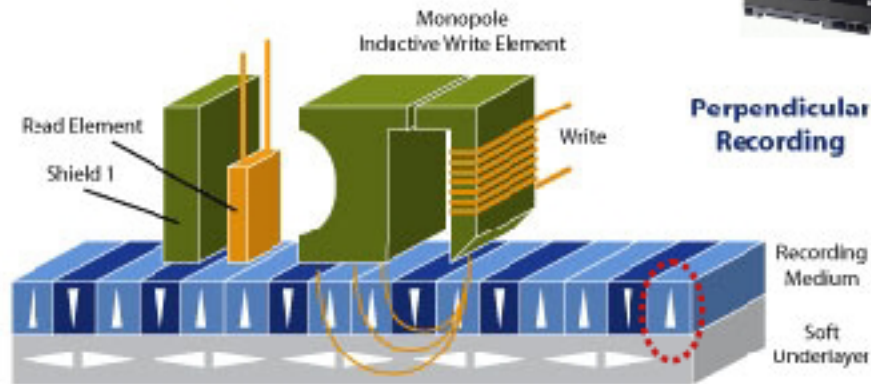
T. Blon¹, N. Liakakos^{1,2}, C. Achkar¹, B. Cormary¹, R. P. Tan¹, G. Chaboussant³, F. Ott³, B. Warot-Fonrose², E. Snoeck², B. Chaudret¹, M. Respaud¹, K. Soulantica¹

¹Laboratoire de Physique et Chimie des Nano-objets (LPCNO), Toulouse

²CEMES-CNRS, Toulouse

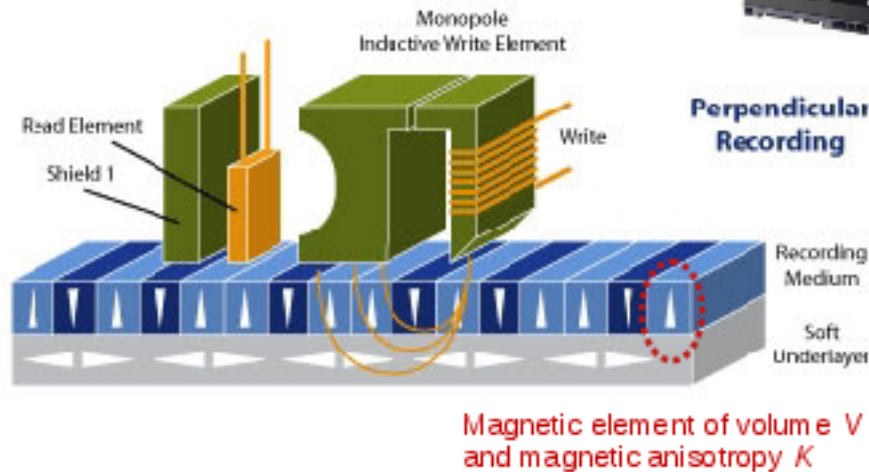
³Laboratoire Léon Brillouin, Gif sur Yvette

Actual technology of Hard Disk Drives: perpendicular magnetic recording (PMR)



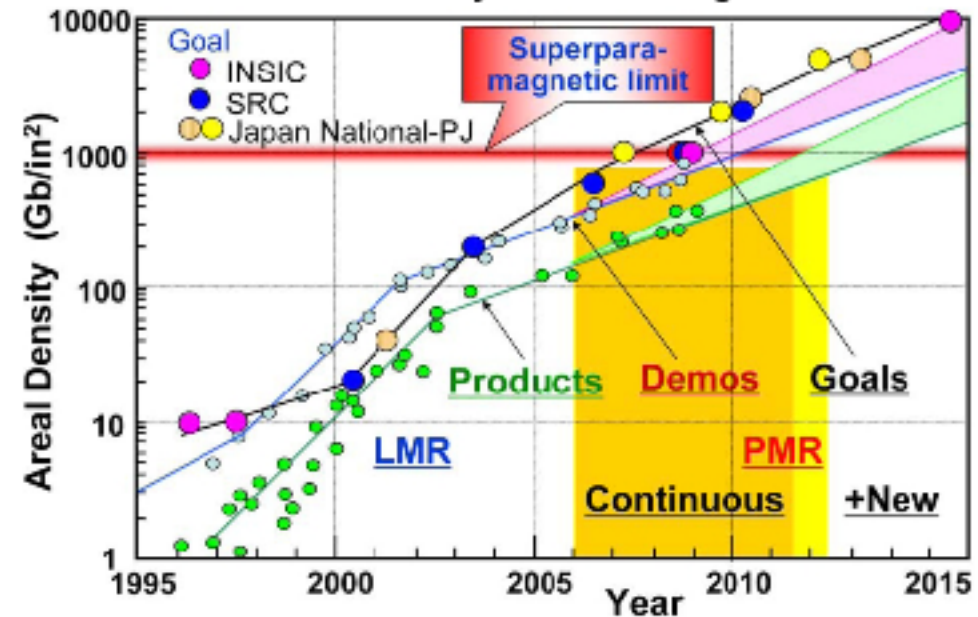
Magnetic element of volume V
and magnetic anisotropy K

Actual technology of Hard Disk Drives: perpendicular magnetic recording (PMR)



Interest of ultra-high density nanomagnets arrays

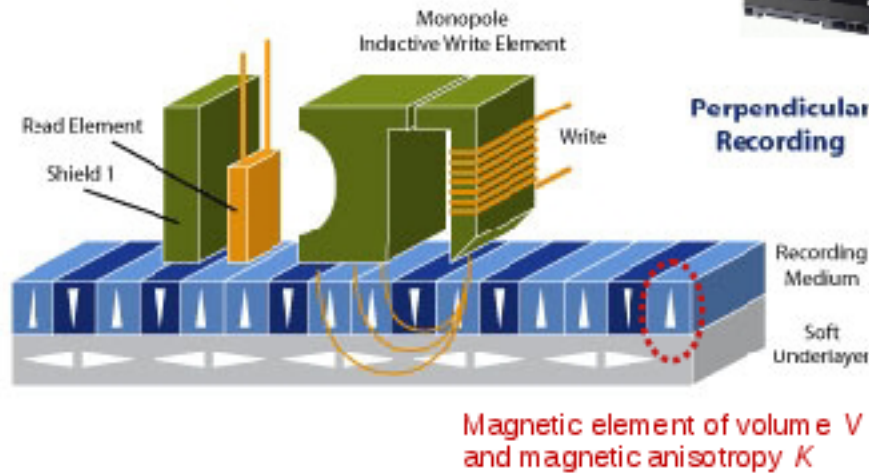
Areal density and R&D targets



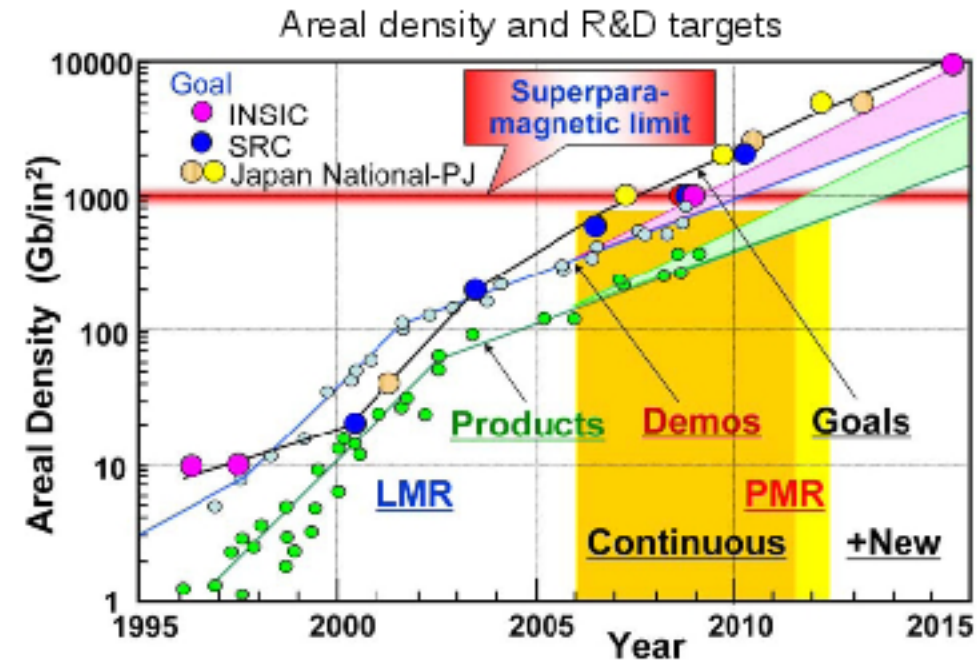
Limitation of the actual technology: superparamagnetic limit

Relaxation time: $\tau = \tau_0 \cdot \exp(KV/k_B T)$ + Magnetic relaxation time > 10 years $\Rightarrow$ High KV product are required ($KV \approx 40 k_B T$)

Actual technology of Hard Disk Drives: perpendicular magnetic recording (PMR)



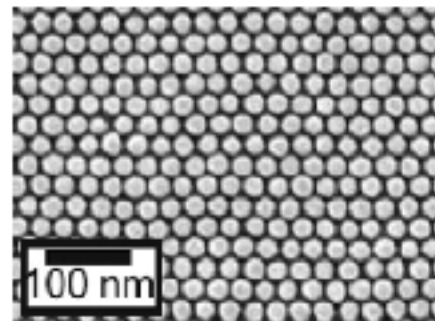
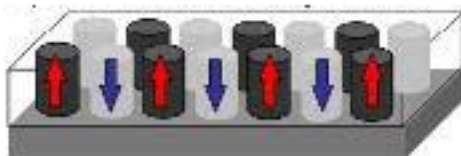
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Alternative technology: Bit Patterned media (BPM)



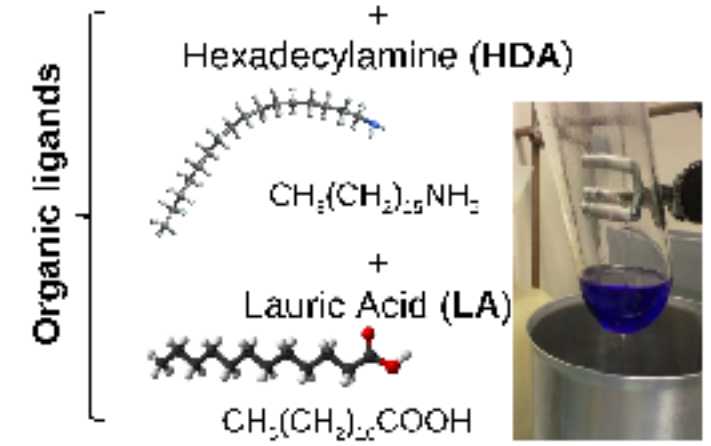
Demo : 1 Tbits/in²

CoCrPt PVD film deposited on a diblock copolymer template

T.R. Albrecht et al. IEEE Trans. Mag. 49(2) 773 (2013)

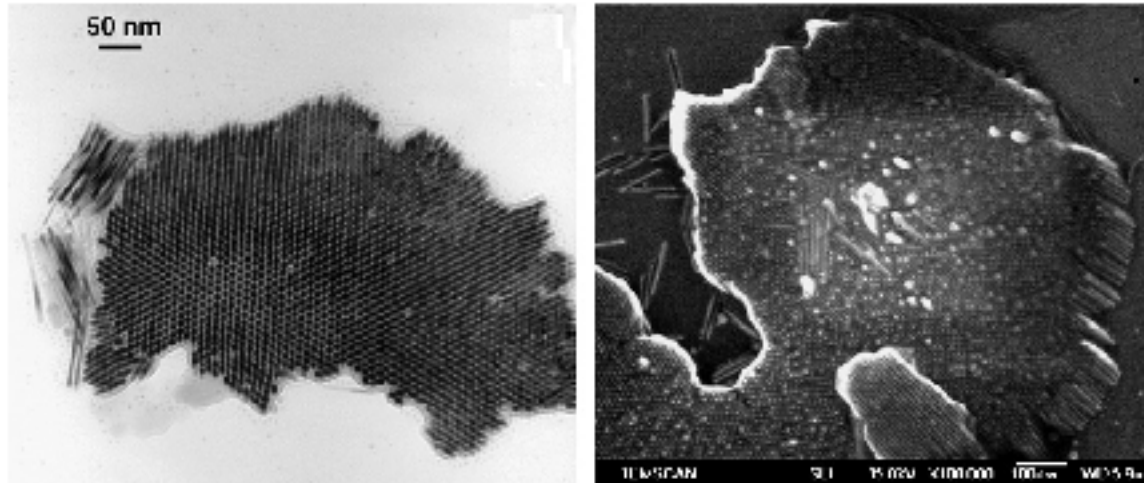
Decomposition of an organo-metallic precursor

Cobalt precursor: $\text{Co}[\text{N}(\text{SiMe}_3)_2]_2$



dissolved in dry anisole under 3bar of H_2

SEM and TEM after 48 hours



Decomposition of an organo-metallic precursor

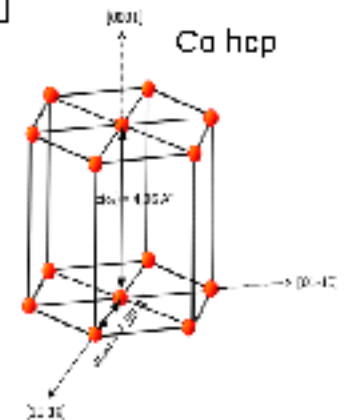
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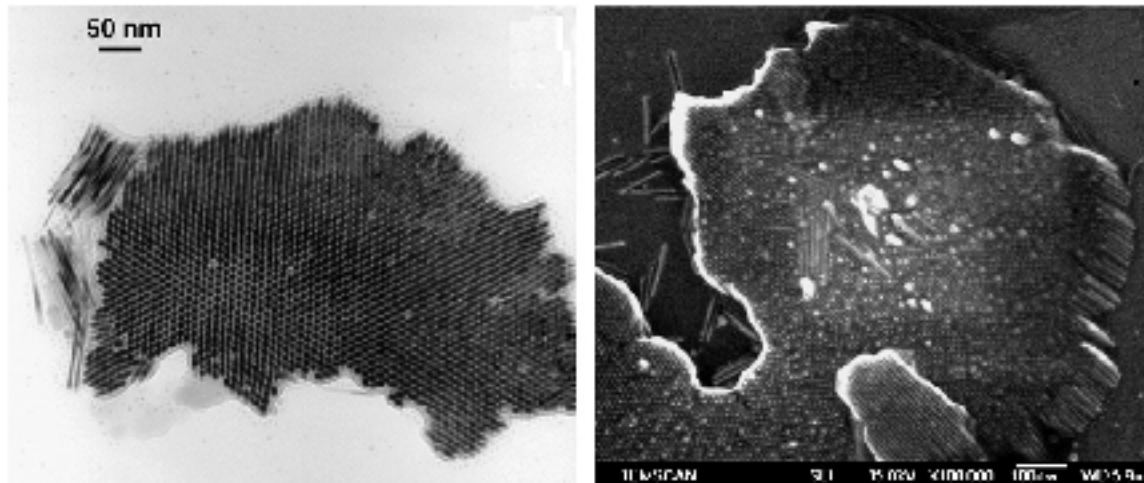
dissolved in dry anisole under 3bar of H_2

Single crystalline Co nanowires

- Length : 40 - 100 nm
- Diameter: 5 - 6 nm
- Single crystalline Co hcp

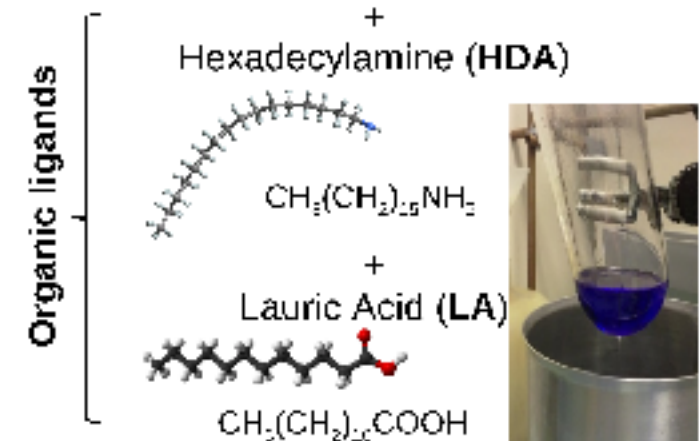


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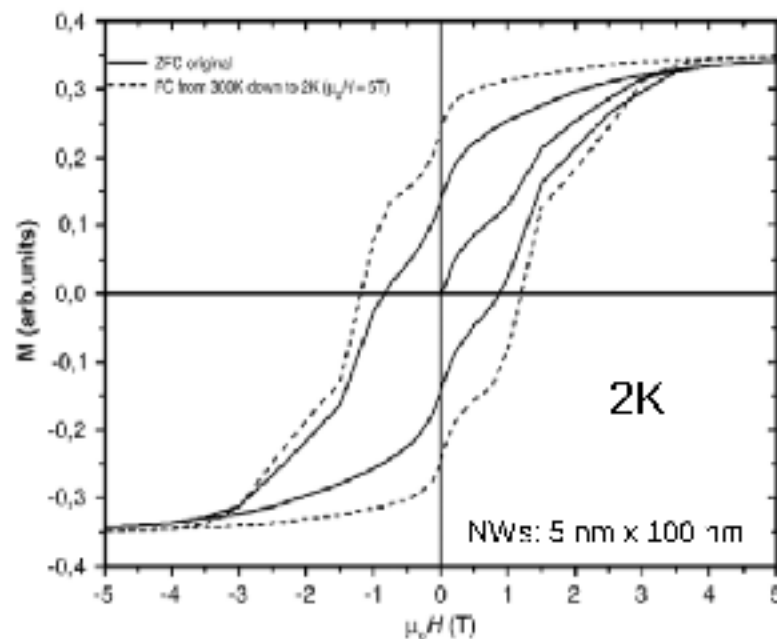


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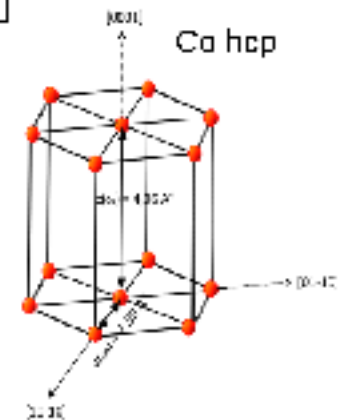
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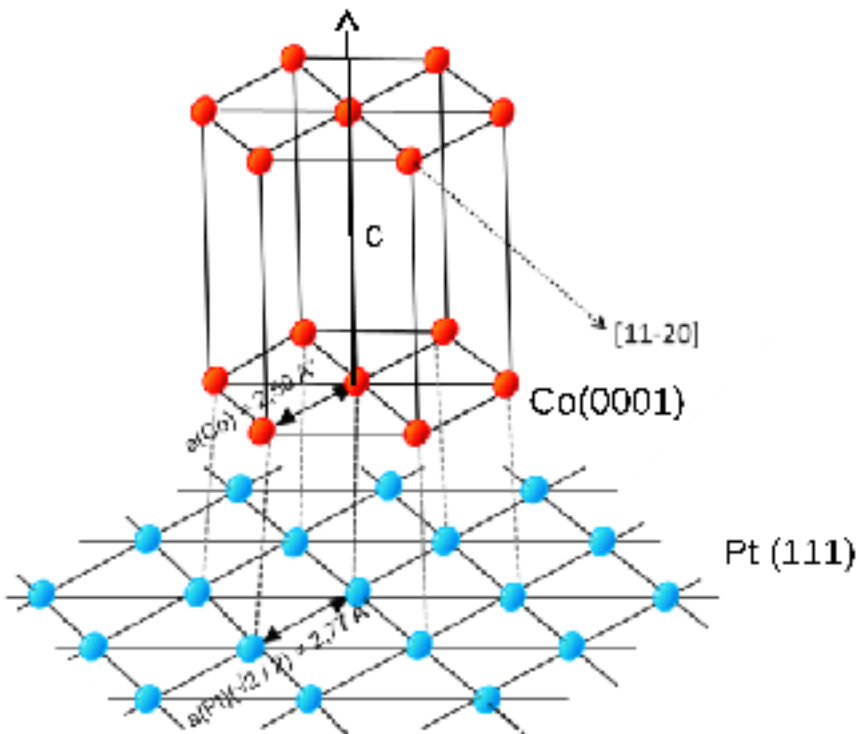
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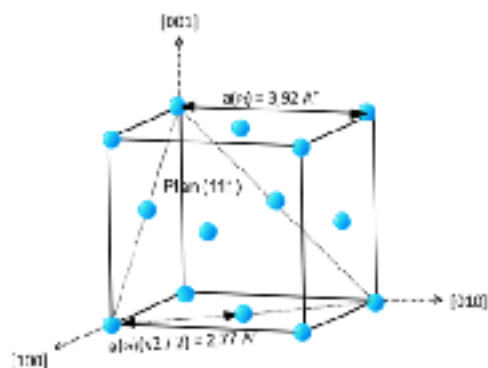
- $\mu_0 H_c @ 2K = 1.2T$
 $\Rightarrow$ Effective anisotropy $K_{eff} = 8 \cdot 10^5 \text{ J/m}^3$
 vs theory: $K_{eff} = K_{shape} + K_{mc} = 11 \cdot 10^5 \text{ J/m}^3$



State of the art of Co(0001) film growth

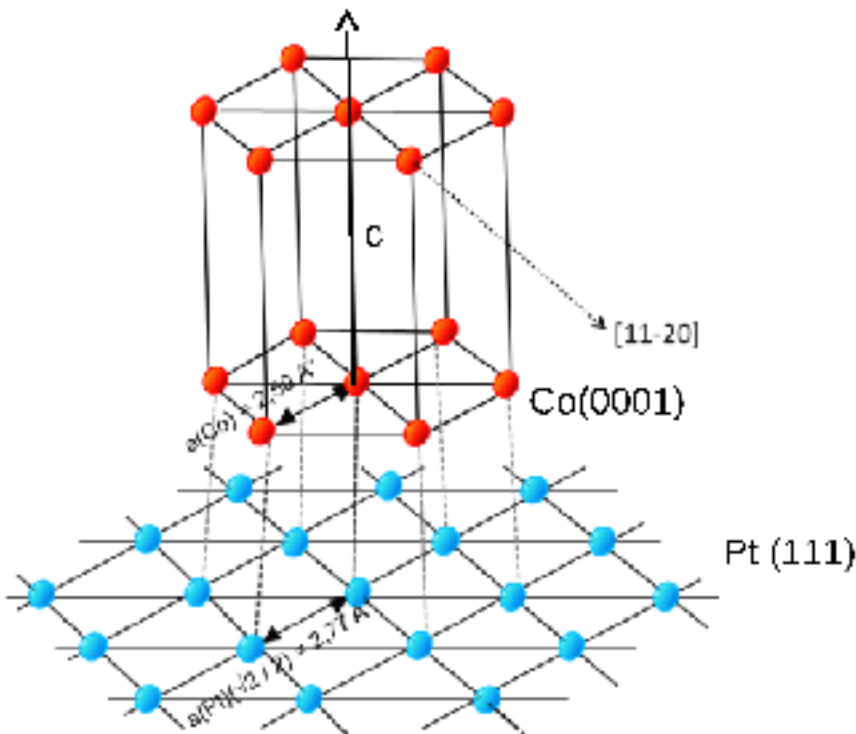


P. Gruber, U.T. Dorig, *Phys Rev B*, **49**, 2021 (1994)
 J. Thiele *Surf. Sci.* **384**, 120-128 (1997)

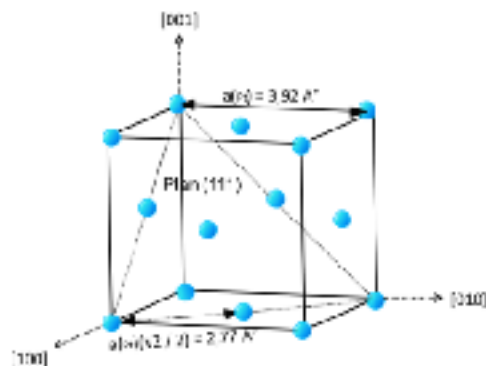


How to organize Co NWs on substrates?

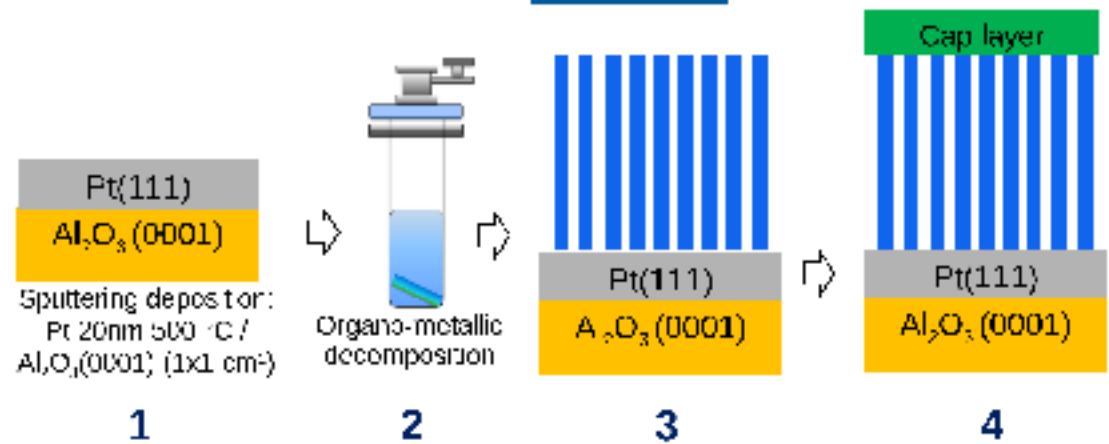
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Process



Set-up



Glove Box

Ar atmosphere
(without H₂O and O₂)

Spin coating, dip coating, hot plate,
electrical measurements, optical microscope

Thin Film deposition chamber

DC and RF sputtering, evaporation,
reactive plasma, annealing



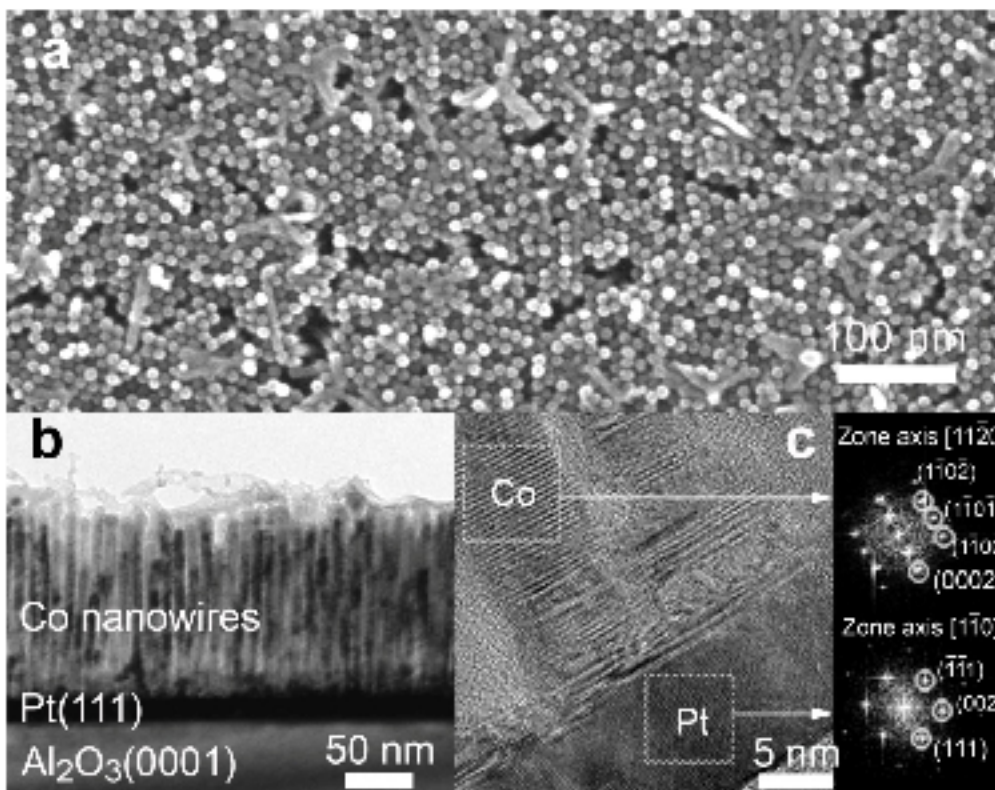
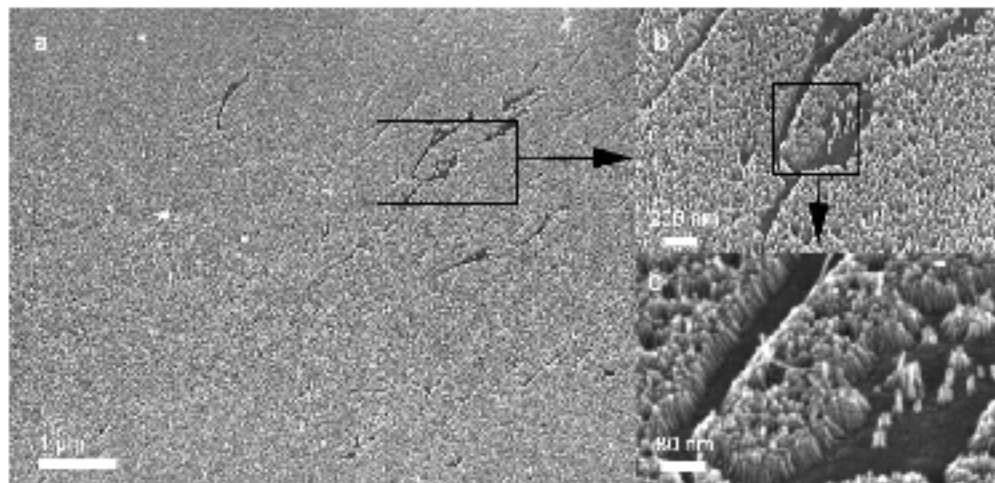
Co NWs / Pt(111)

Conditions 1

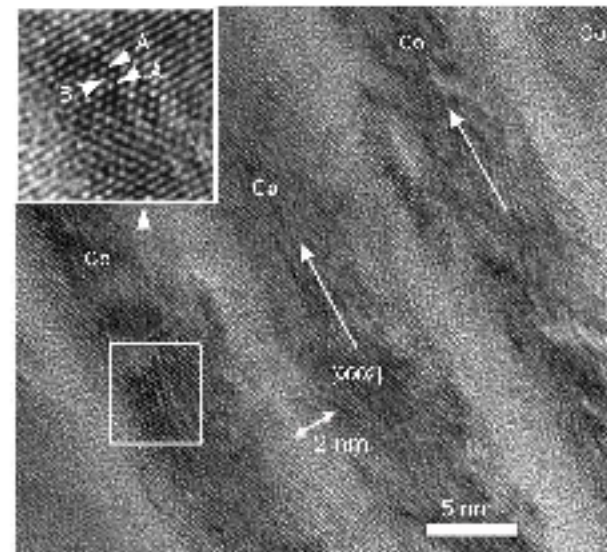
Co/LA/HDA=1/1.2/1.2 ; 100°C, 3
bars of H₂, 4.5 days of reaction

Co/LA/HDA=1/1.2/1.2 ; 100°C, 3 bars of H₂, 4.5 days of reaction

- 8 nm in diameter
- 150 nm in length
- 2 nm inter-NWs distance
- single-crystalline Co hcp
- epitaxial Co NW growth: Co(0001) [11-20] // Pt(111) [2-20]

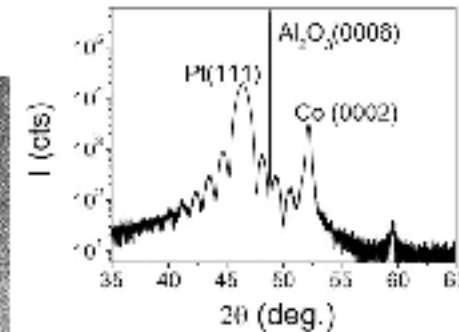


Electron microscopy

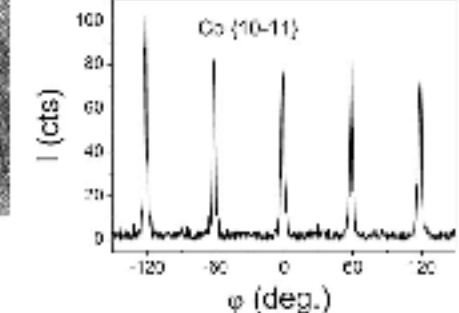


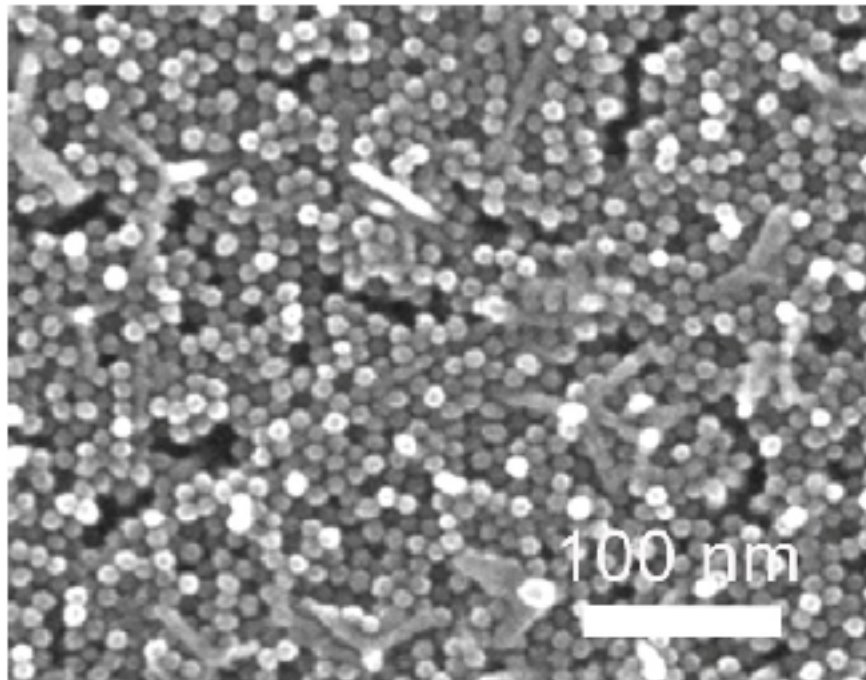
XRD

Symmetric θ -2 θ scan

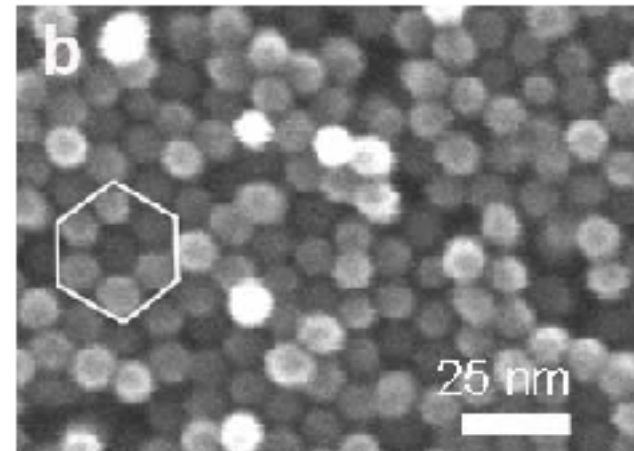


ϕ scan Co{10-11}

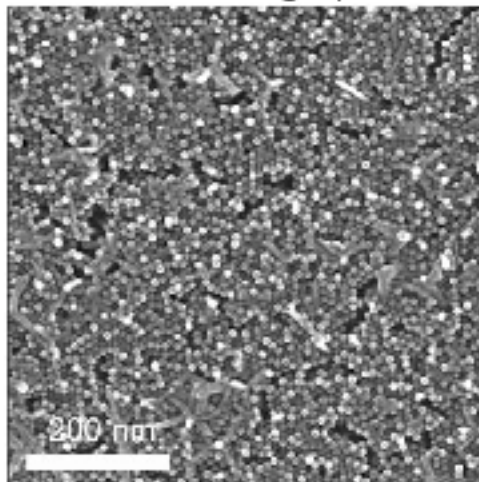




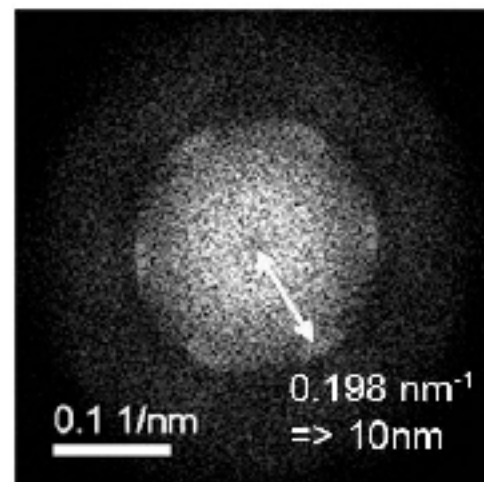
SEM micrographs



SEM micrograph



FFT



=> hexagonal array with a
10 nm periodicity
=> **7×10¹² NWs/in²**

7 T-wires/in² Co NW arrays

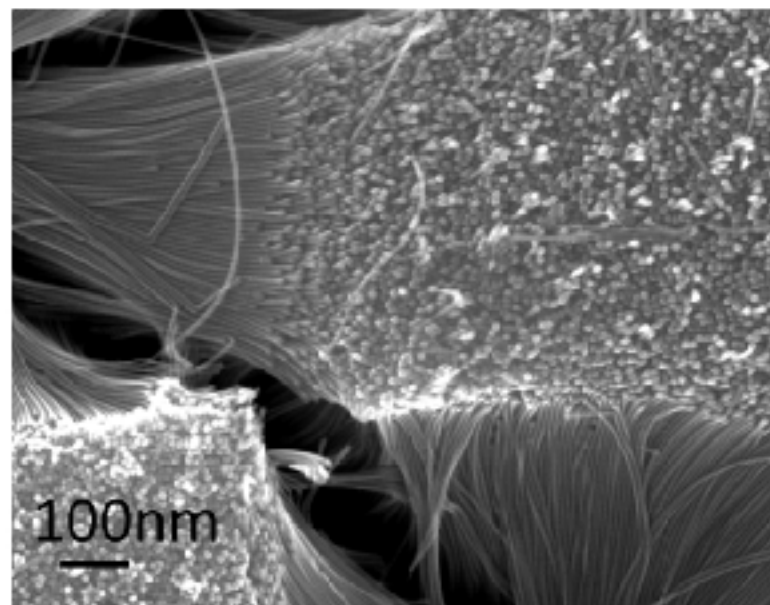
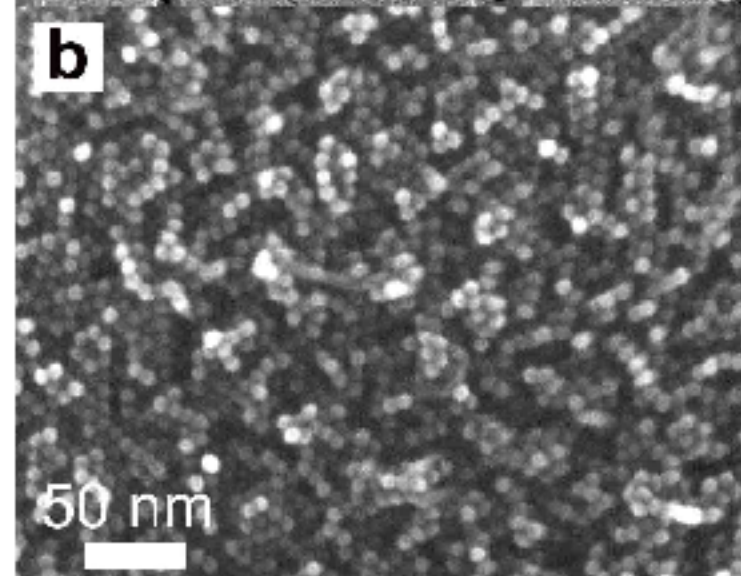
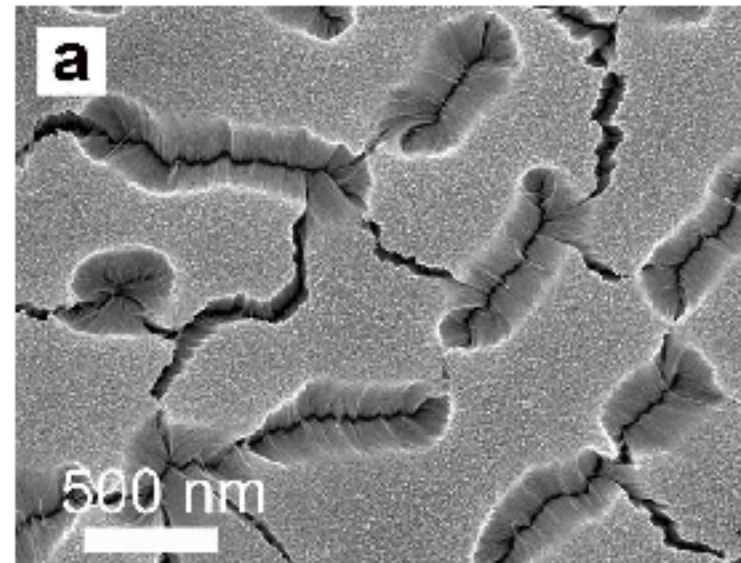
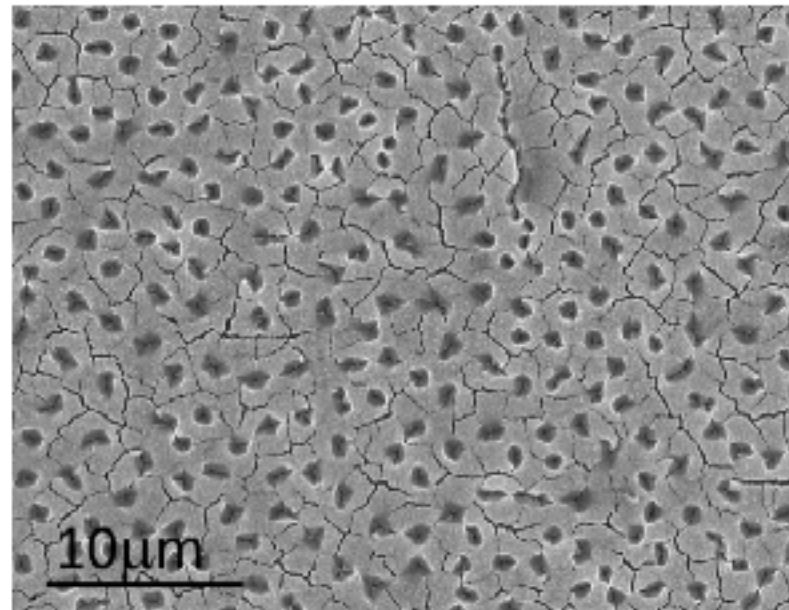


Co NWs / Pt(111)

Conditions 2

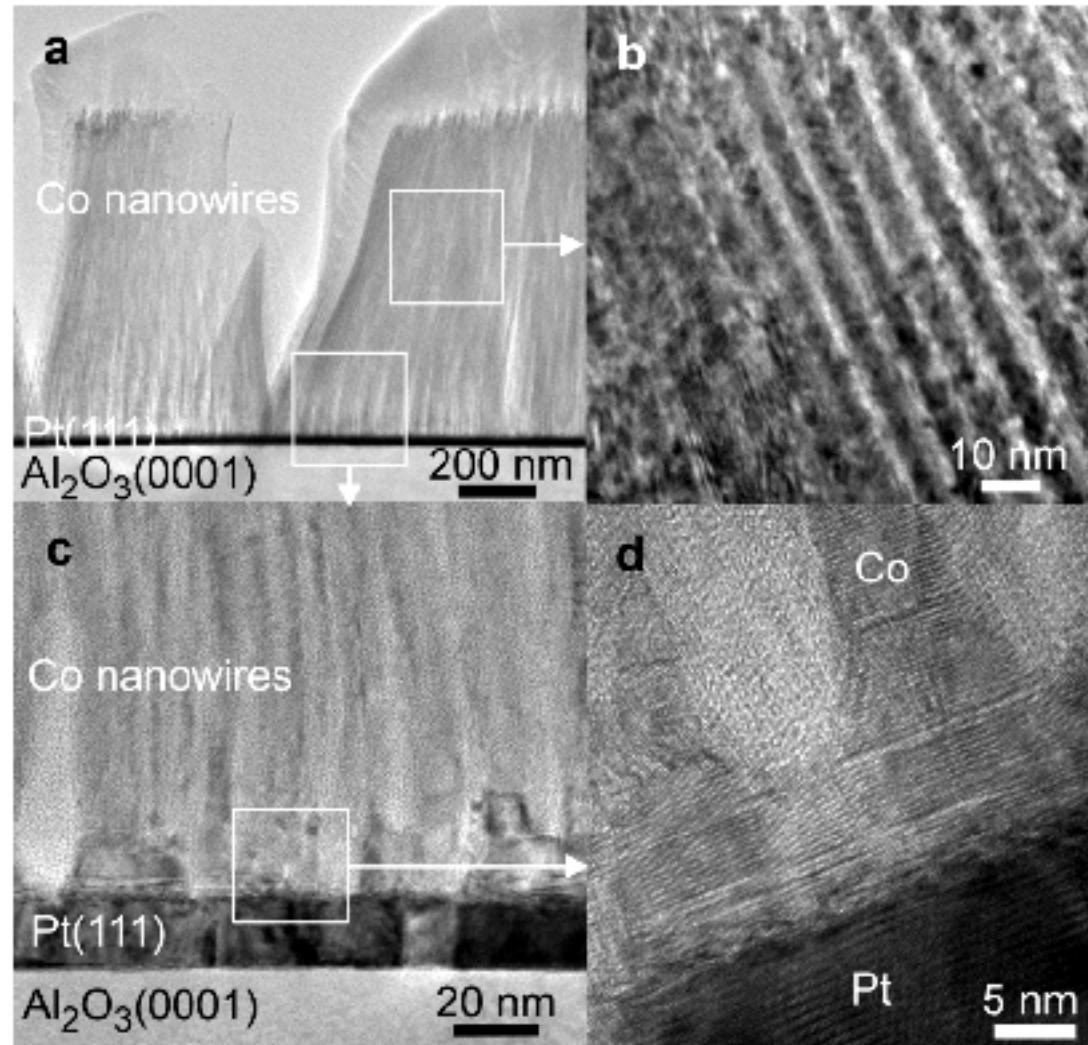
Co/LA/HDA=1/2/2 ; 150°C, 3 bars
of H₂, 24h of reaction

SEM micrographs

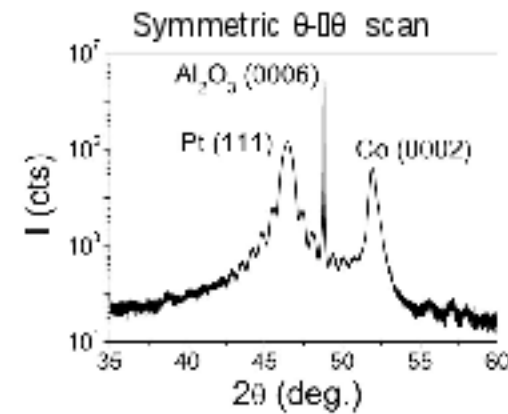


Co/LA/HDA=1/2/2 ; 150°C, 3 bars of H₂, 24h of reaction

TEM micrographs

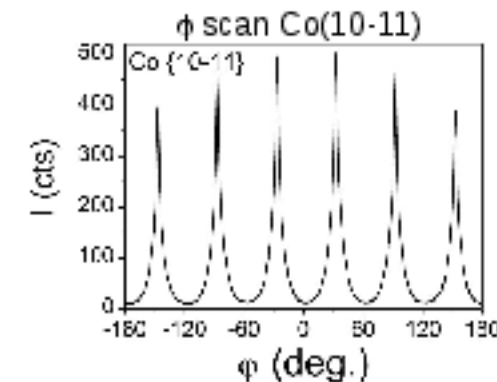
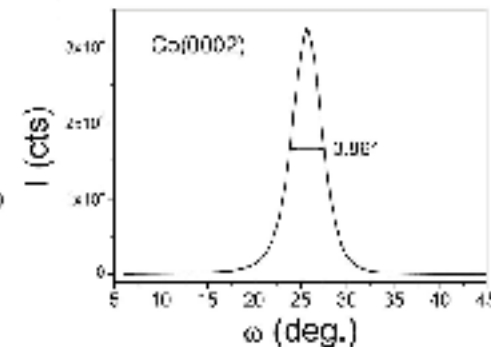


- 5-6 nm in diameter
- 960 nm in length
- 2 nm inter-NWs distance
- single-crystalline Co hcp
- epitaxial Co NW growth: Co(0001) [11-20] // Pt(111) [2-20]
- Low dispersion of the NW axis: $\pm 2^\circ$



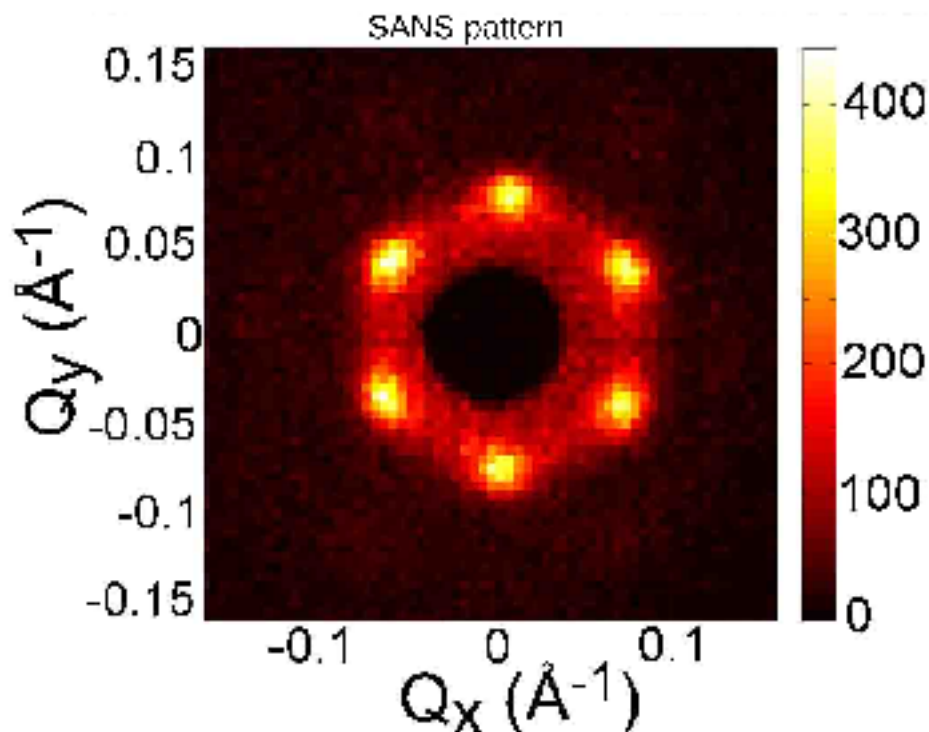
XRD

Rocking curve Co(0002)

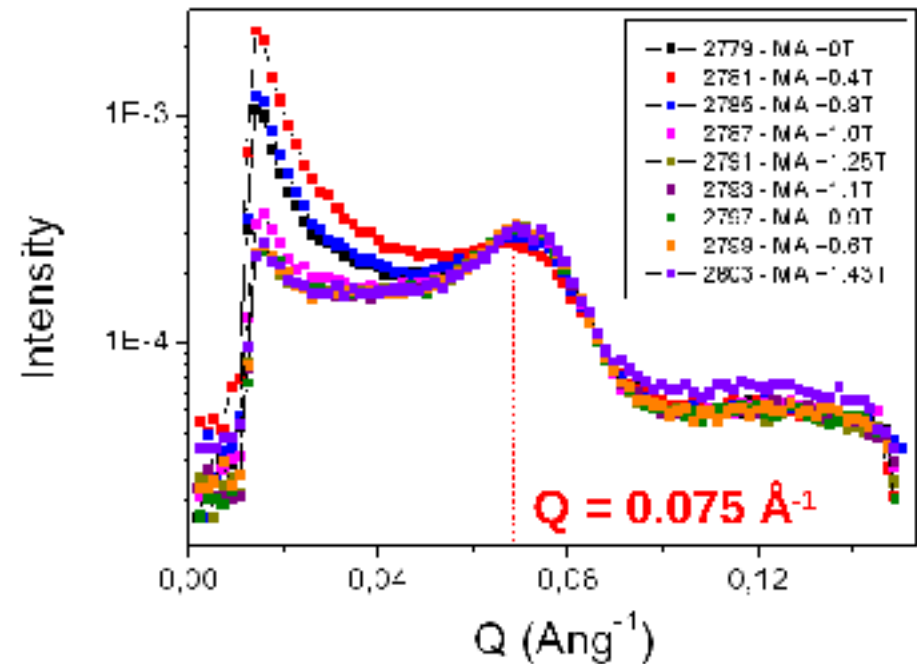


Small angle neutron scattering (SANS)

PAXY spectrometer at the Laboratoire Léon
Brillouin / Orphée, Saclay, France



Integration circulaire de l'intensité diffusée



Array periodicity : $P = 2\pi / Q = 8.4 \text{ nm}$

⇒ density : $10.3 \times 10^{12} \text{ NWs/in}^2$

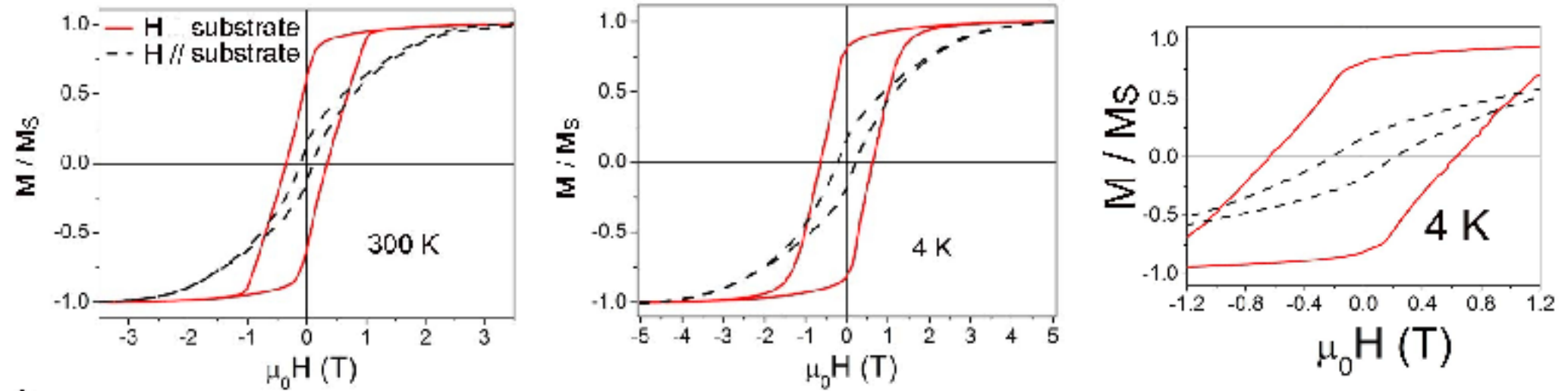
⇒ packing fraction $P = 0.38$



Collaboration: F. Ott, G.
Chaboussant, LLB-CEA

10 T-wires/in² Co NW arrays

Hysteresis loops (VSM)

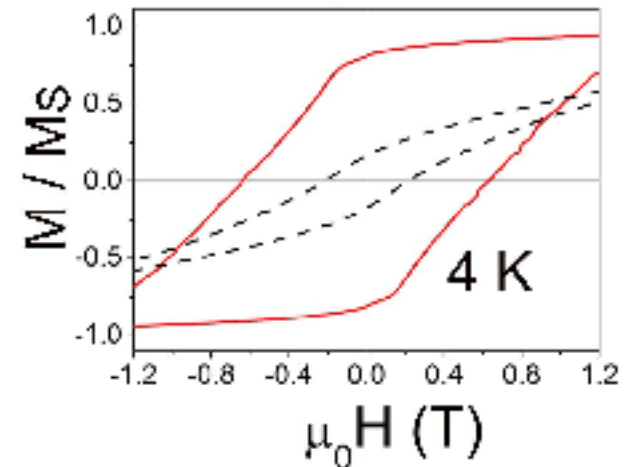
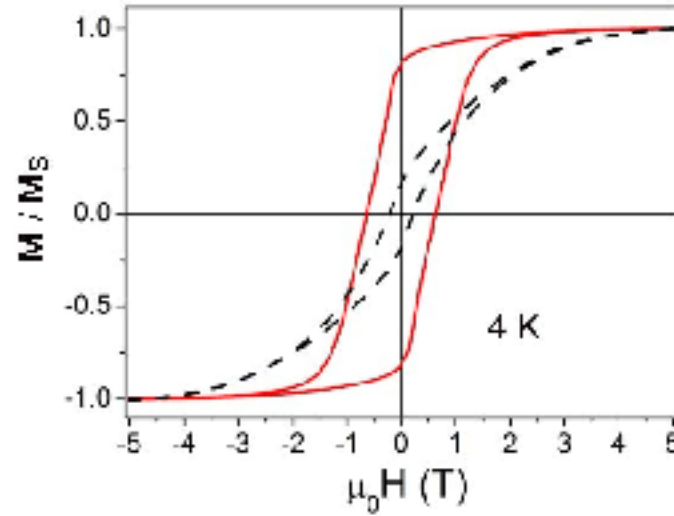
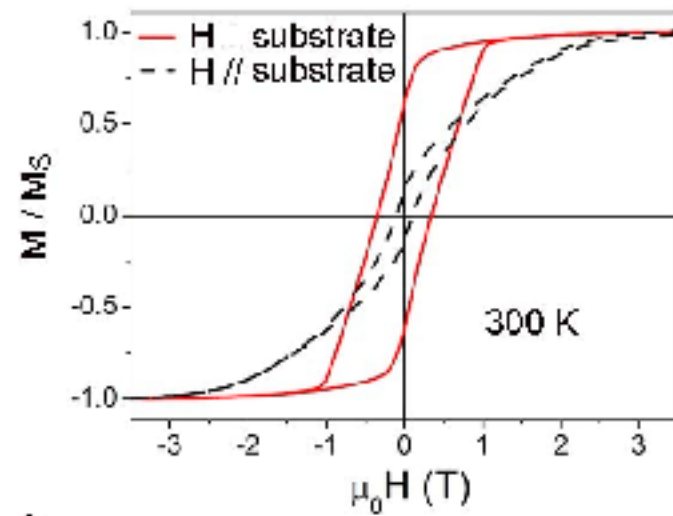


- **300K:** $\mu_0 H c^\perp = 0.35$ T and $M_r/M_s^\perp = 0.61$
 $\mu_0 H c^\parallel = 0.10$ T and $M_r/M_s^\parallel = 0.14$

- no exchange bias after FC (5T 300K $\rightarrow$ 4K)
 $\Rightarrow$ no Co oxidation

- **4K:** $\mu_0 H c^\perp = 0.62$ T and $M_r/M_s^\perp = 0.81$
 $\mu_0 H c^\parallel = 0.21$ T and $M_r/M_s^\parallel = 0.17$

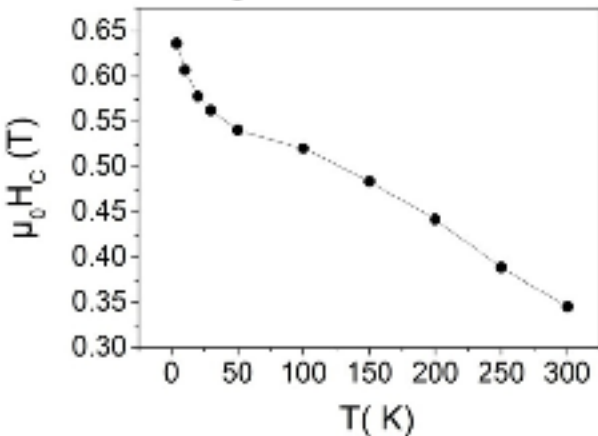
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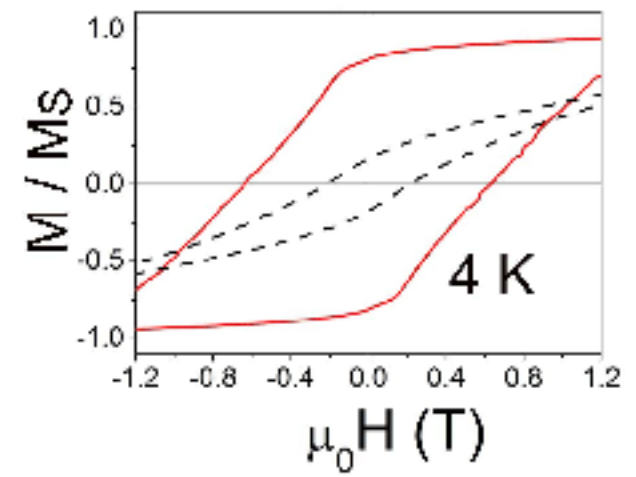
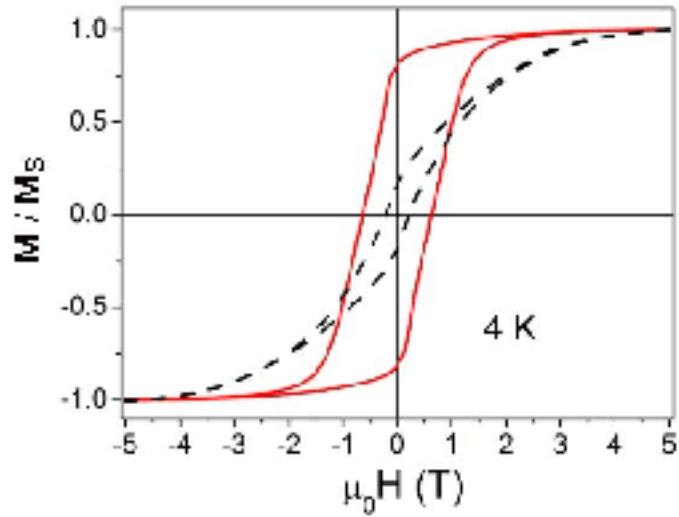
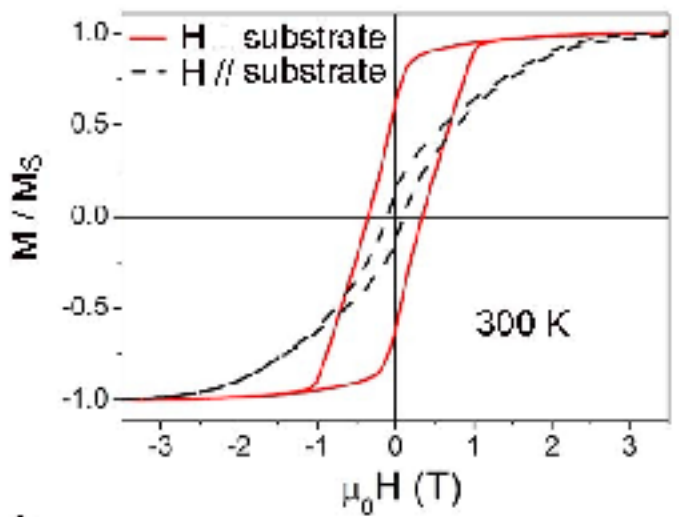


Impossibility to fit the
data with the Sharrock
formula :

$$H_c = H_0 \left[1 - \frac{n \epsilon / \tau_0 k_B T}{K(T) V} \right]^{1/m}$$



Hysteresis loops (VSM)

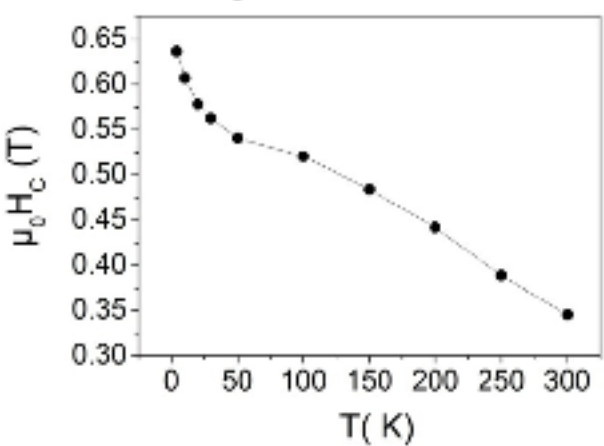


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 $\mu_0 H_{c\parallel} = 0.21$ T and $M_r/M_s^\parallel = 0.17$

- saturation magnetization: 7.1×10^{-3} emu.
using bulk M_s => $P = 0.42$



Impossibility to fit the data with the Sharrock formula :

$$H_c = H_0 \left[1 - \frac{(\ln(t/\tau_0) k_B T)^{1/m}}{K(T)V} \right]$$

- slope of hysteresis loop at H_c : $\left[\frac{dM}{dH} \right]_{H_c} \approx 1/P$
=> $P = 0.40$

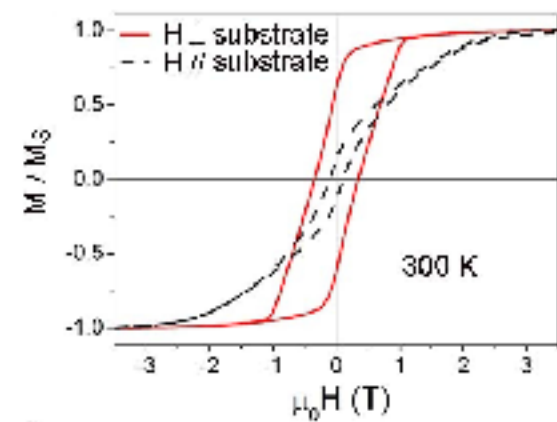
- Measured perpendicular magnetic anisotropy (300 K):

$$K_{eff} = 9.3 \cdot 10^5 \text{ J/m}^3$$

- Theoretical magnetic anisotropy:

$$K_{eff} = K_{mc} + \frac{\mu_0 M_S^2}{4} (1 - 3P) = 4.5 \times 10^5 \text{ J/m}^3$$

⇒ Difference between exp. and expected anisotropies: dipolar interactions



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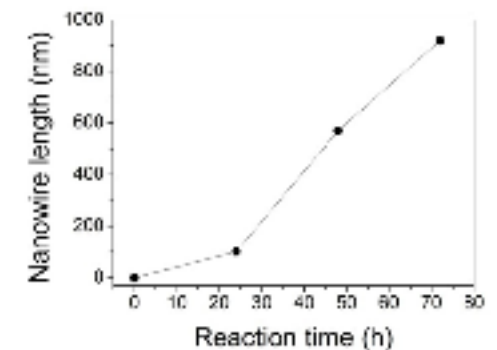
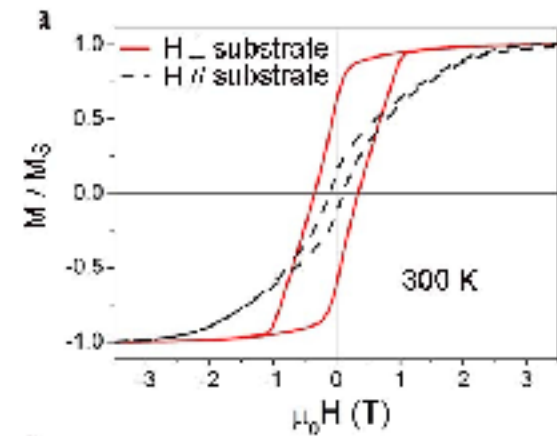
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⇒ Difference between exp. and expected anisotropies: dipolar interactions

- $K_{eff} V \approx 4000 \times k_B T$ (using $T=350\text{K}$, a typical magnetic media working temperature)

⇒ Possibility to reduce the nanowire volume V



Nanowire length measured by TEM as a function of the reaction time (Co/LA/HDA ratio : 1/2/2, 110°C).

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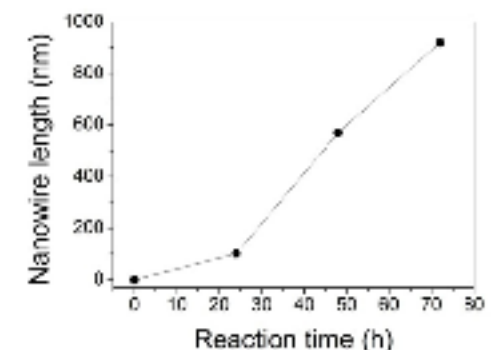
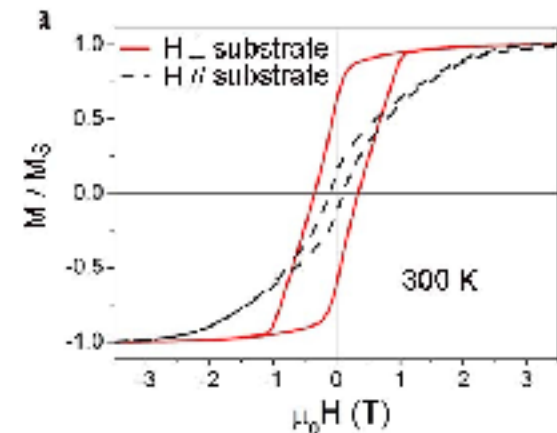
⇒ Possibility to reduce the nanowire volume V

- Magnetic media requirements**

- very low surface roughness
- protection of the active layer with an adequate protective layer

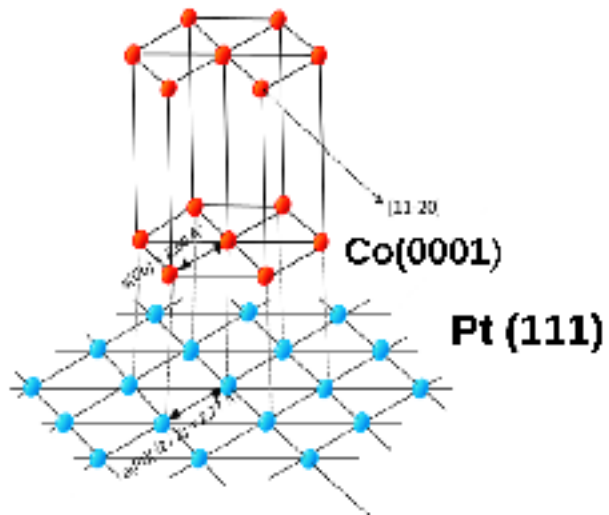
- Read/write process:**

- Read/write methods are proposed for 10Tbits/in² (shingled writing and two-dimensional readback and signal processing)
- bundles of several NWs => several Tbits/in² media

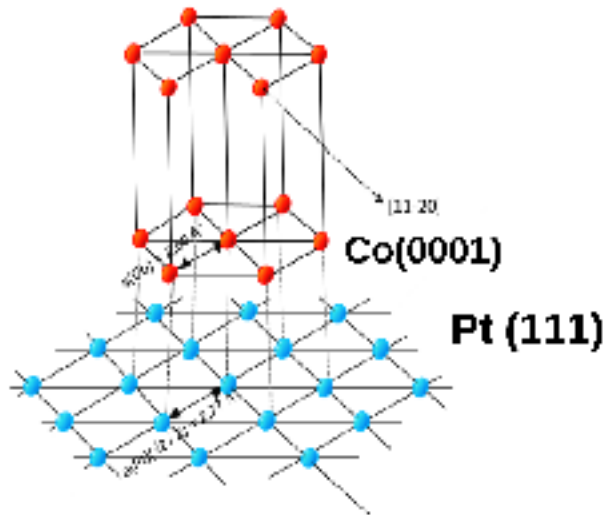


Nanowire length measured by TEM as a function of the reaction time (Co/LA/HDA ratio : 1/2/2, 110°C).

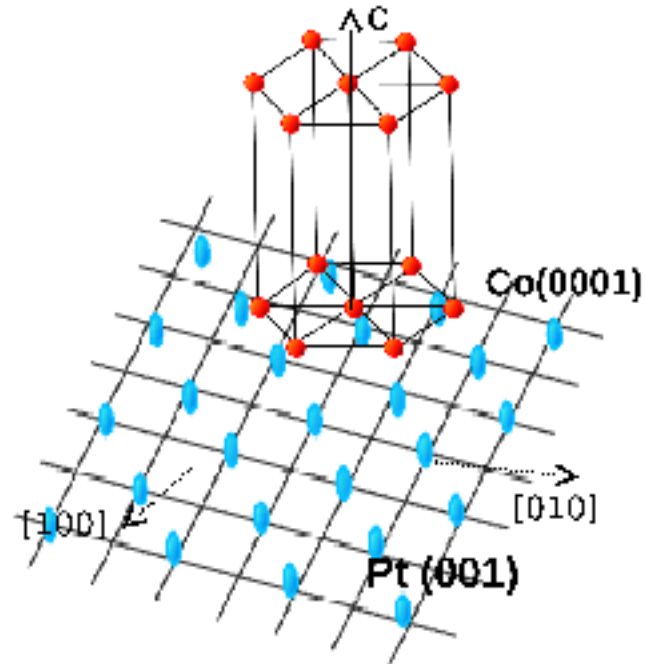
Co(0001) NW growth on a
6-fold symmetry surface



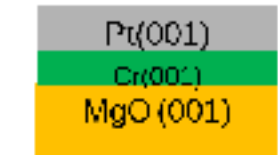
Co(0001) NW growth on a 6-fold symmetry surface



Co(0001) NW growth on a 4-fold symmetry surface ?

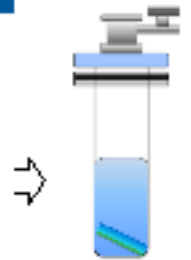


Process



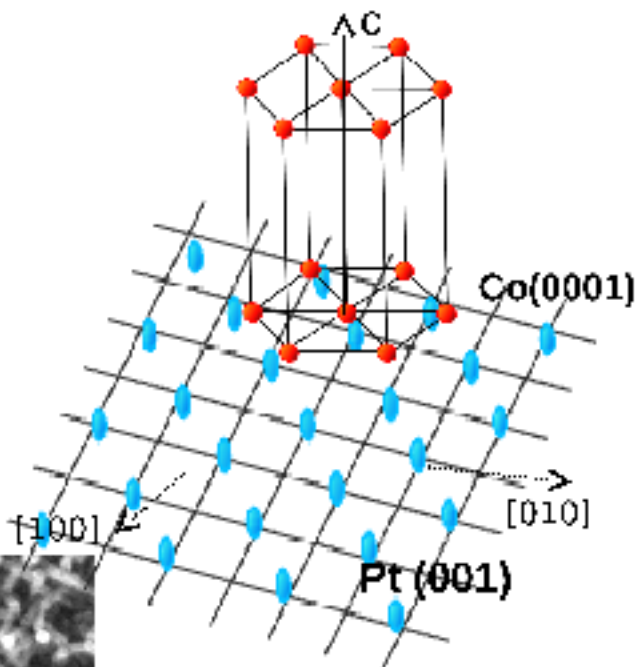
Sputtering deposition:
Pt 20nm 360 °C / Cr 5nm
360°C / MgO(001)

1

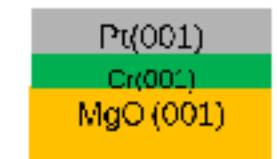


2

Co(0001) NW growth on a 4-fold symmetry surface ?

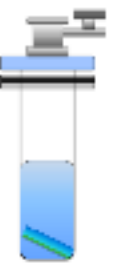


Process

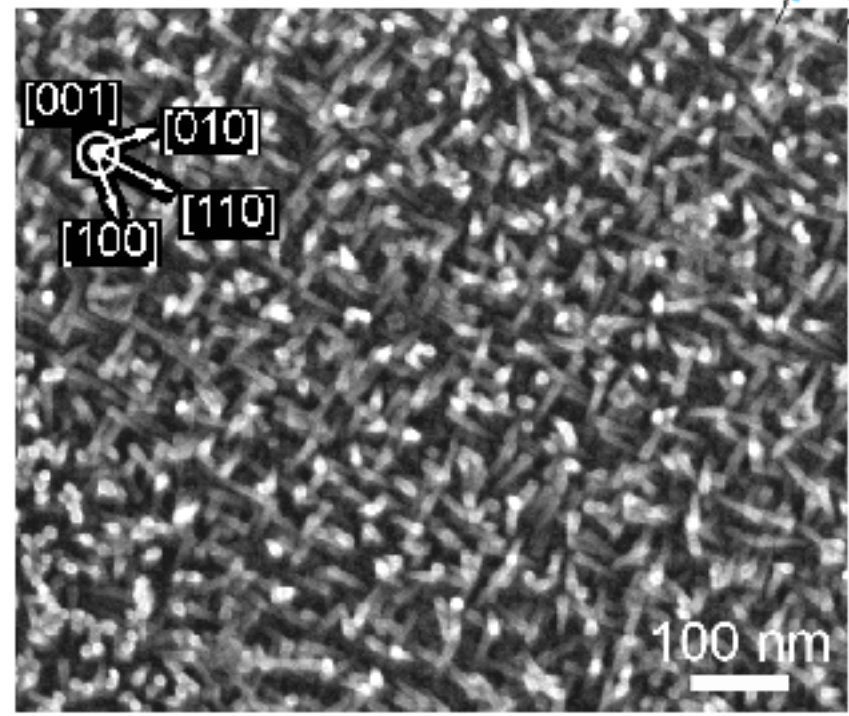


Sputtering deposition:
Pt 20nm 360 °C / Cr 5nm
360°C / MgO(001)

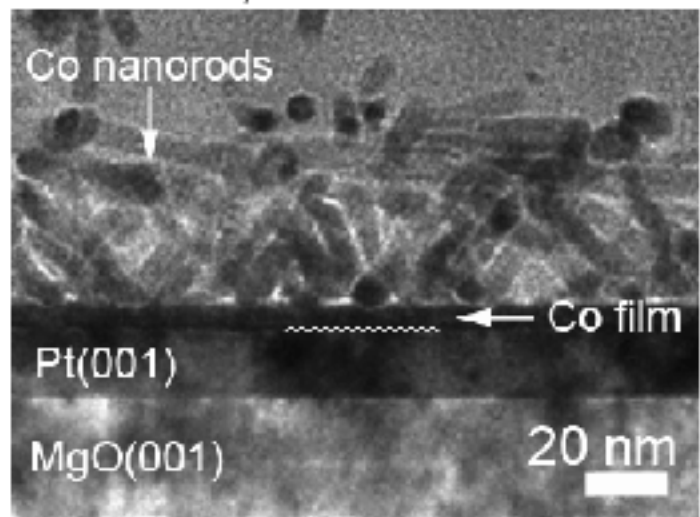
1



2

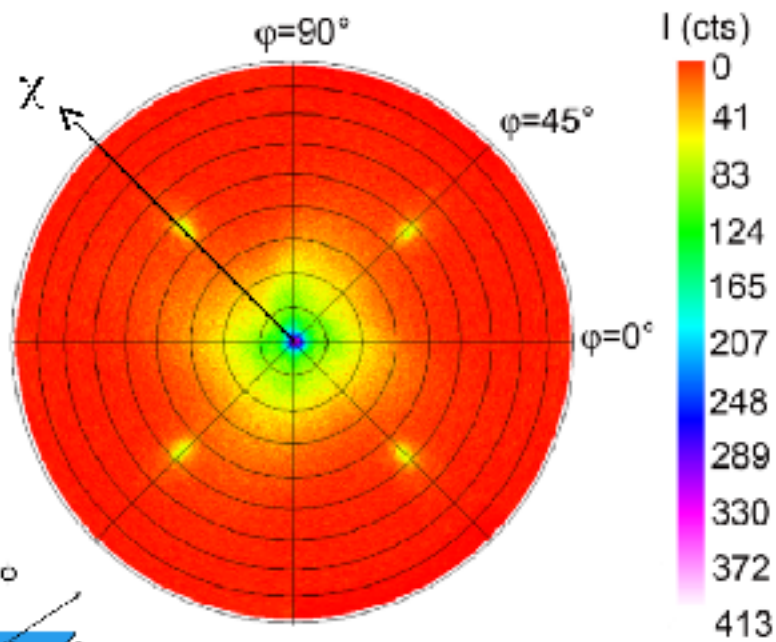


SEM

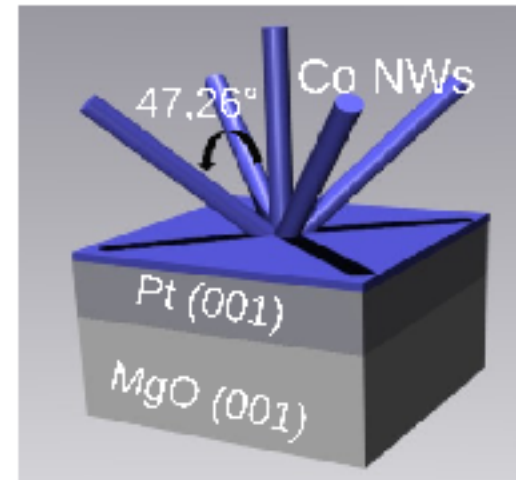
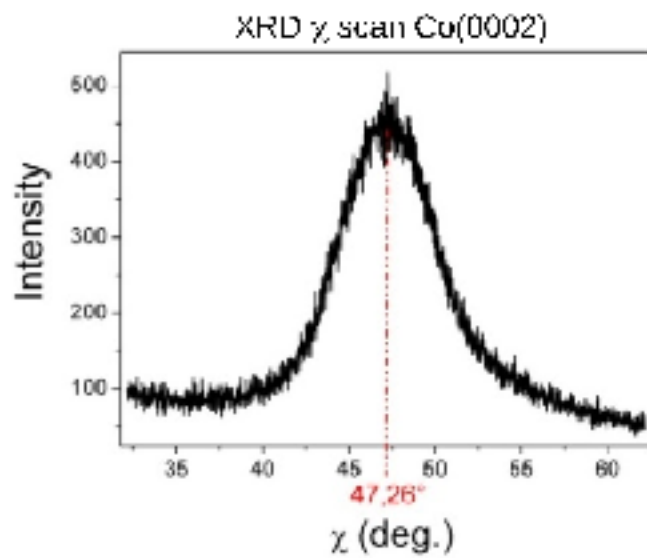


TEM

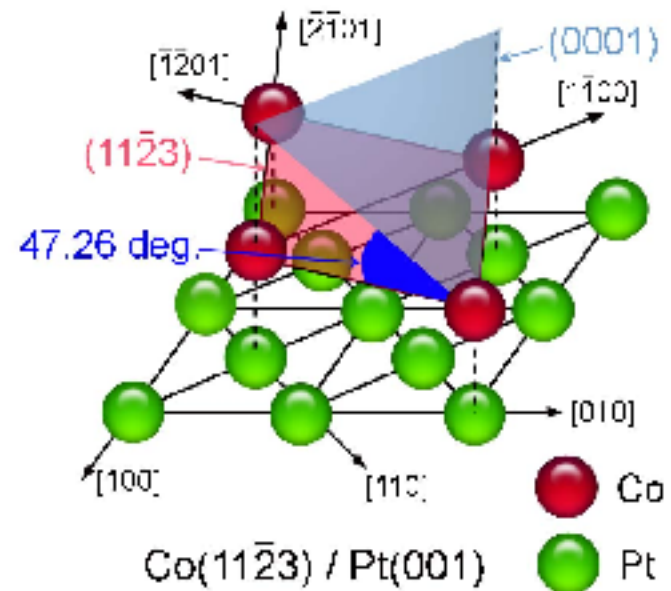
**Tilted growth
of Co
nanowires on
Pt(001)**

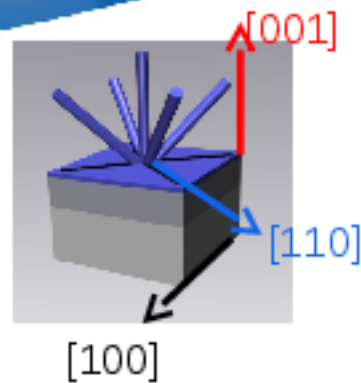


XRD pole figure Co(0002) reflection

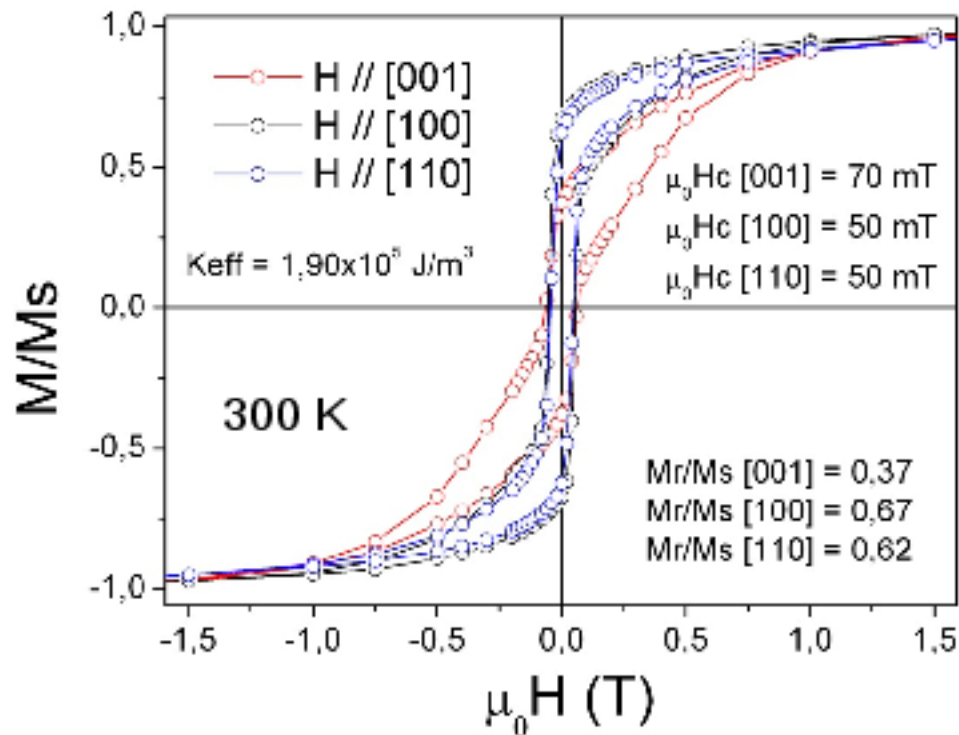


Hypothesis: Co (11-23) // Pt(001)

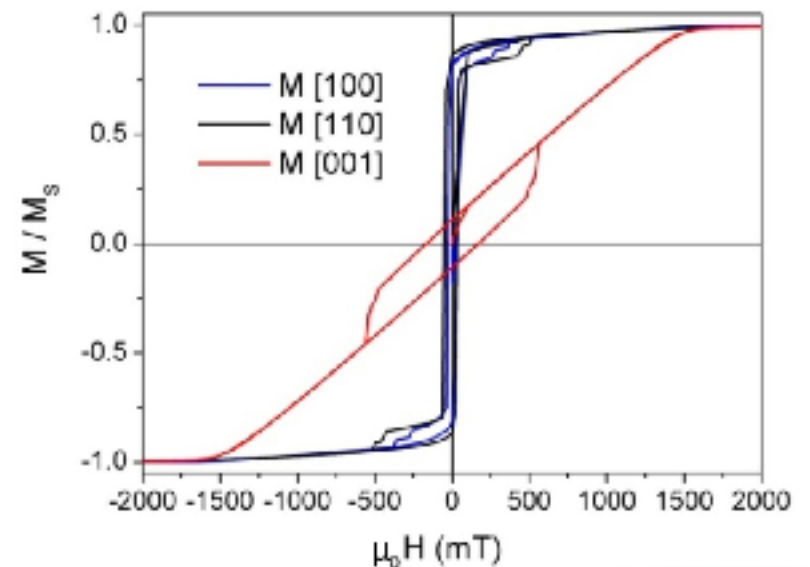
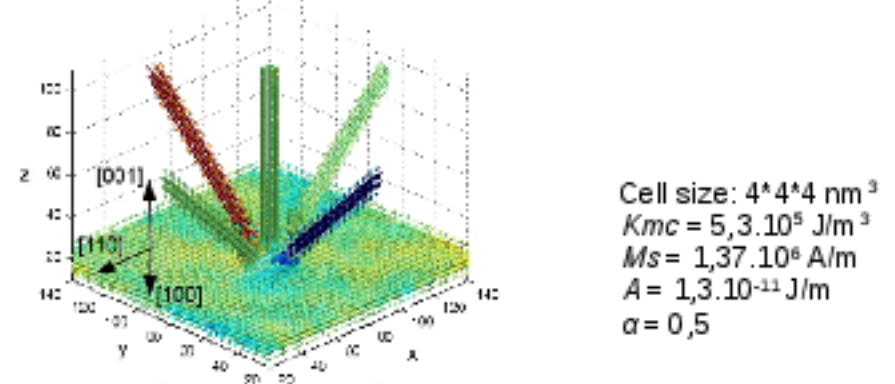




Hysteresis loops (SQUID)



Micromagnetic calculation (OOMMF code)



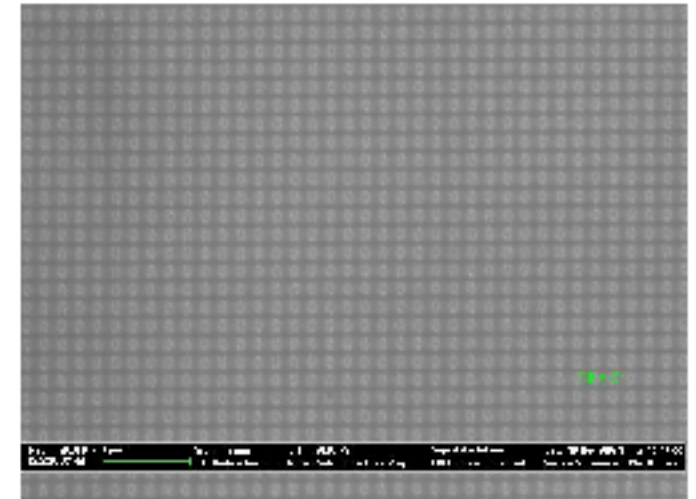


Localization of the Co NW growth

- Co NW growth does not occur on bare Al_2O_3

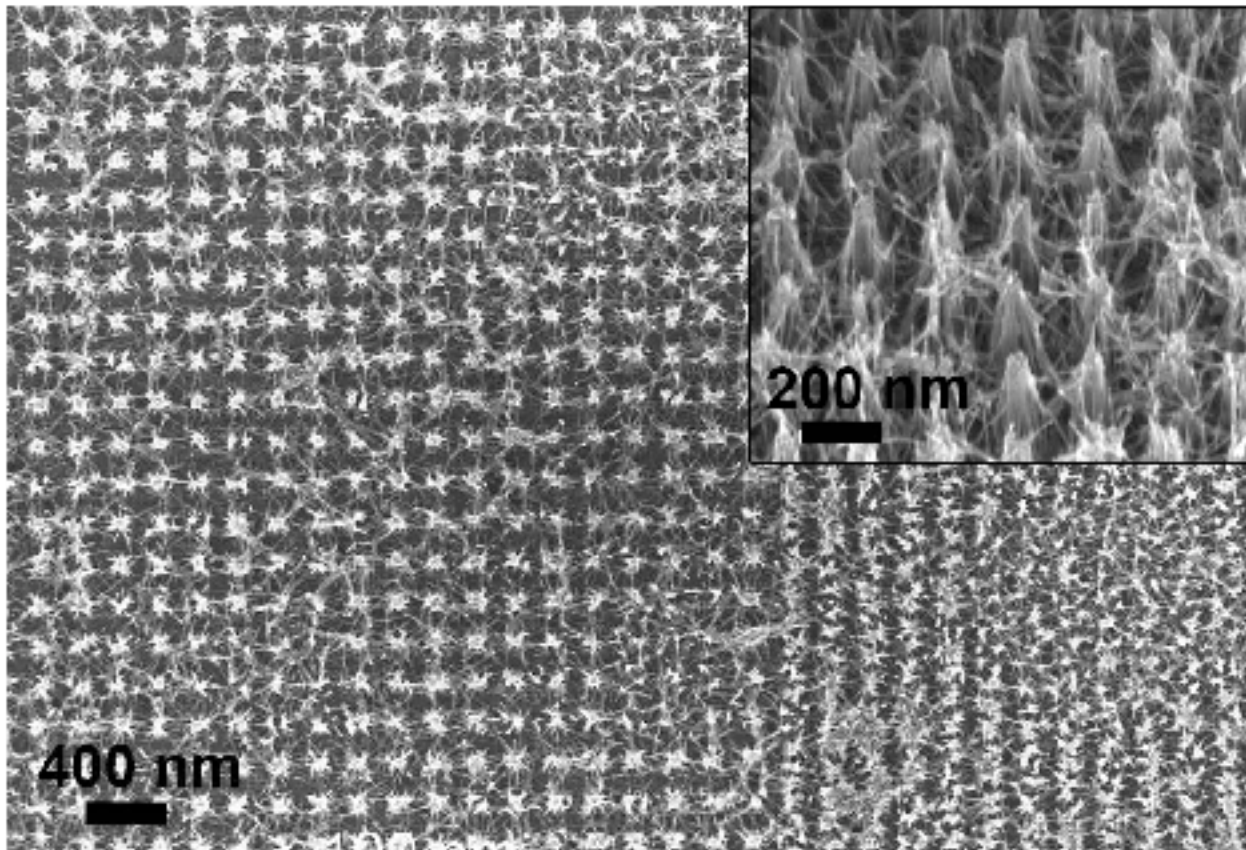
- Co NW growth does not occur on bare Al_2O_3
 ⇒ Co NW growth on predefined positions :

FIB patterned Pt(111) films: 100 x 100 nm² islands

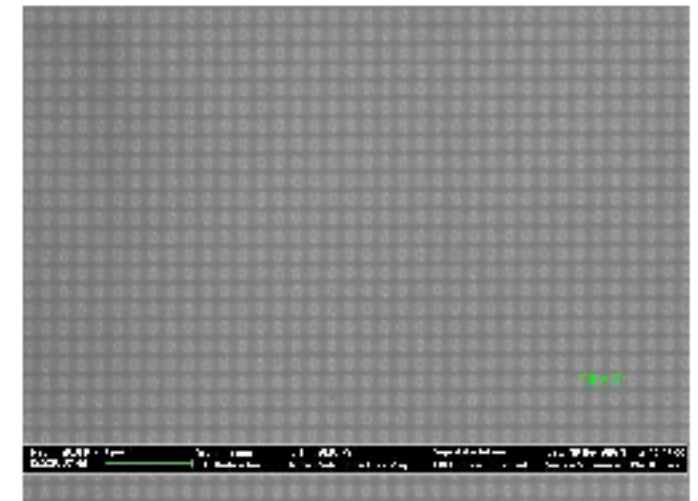


- Co NW growth does not occur on bare Al_2O_3
- ⇒ Co NW growth on predefined positions :

Co NWs grown on a FIB patterned Pt(111) film



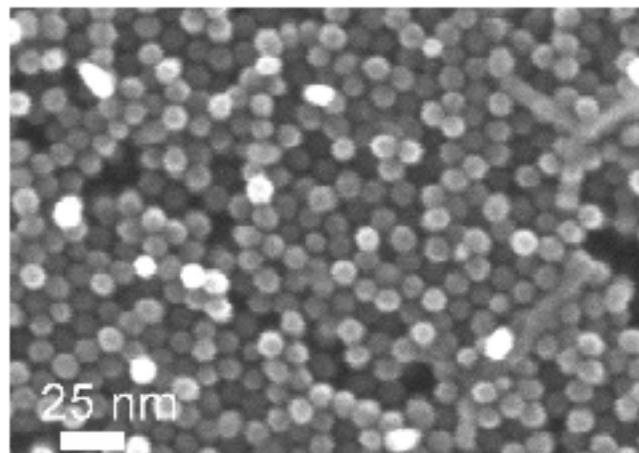
FIB patterned Pt(111) films: 100 x 100 nm² islands



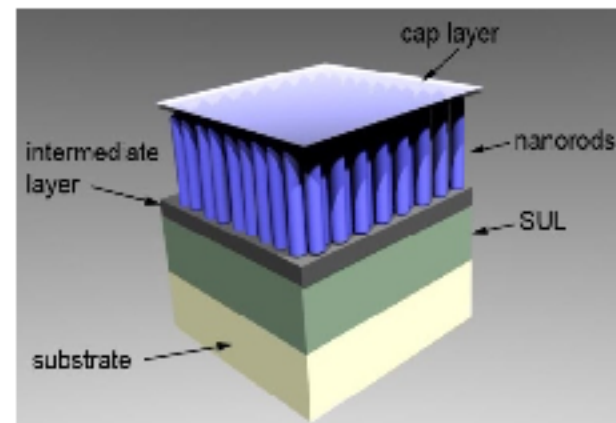
10 Tera-bits-per-square-inch arrays of self-organized, single crystalline 1D nanomagnets

- Nanowire arrays of ultra-high densities on large 2D surfaces (1 cm^2)
- Diameter $< 10 \text{ nm}$
- Single crystalline 1D nanomagnets ferromagnétiques $\Rightarrow$ high perpendicular anisotropy
- Low cost and scalable process

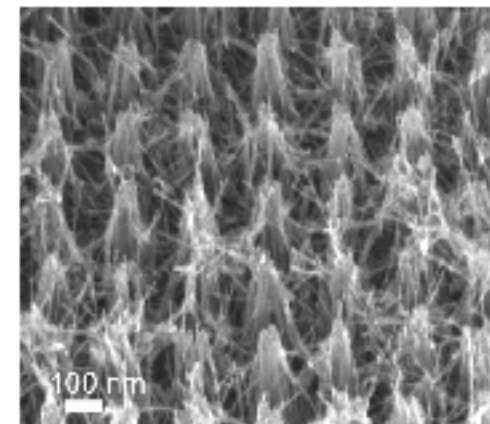
Understanding of the growth mechanism



Promising technology for future magnetic media



New bottom-up method for nano-object self-organization



10 Tera-bits-per-square-inch arrays of self-organized, single crystalline 1D nanomagnets

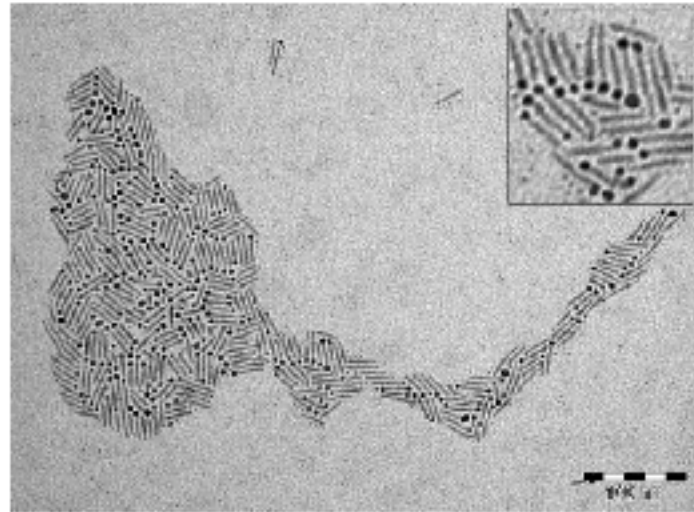
T. Blon¹, N. Liakakos^{1,2}, C. Achkar¹, B. Cormary¹, R. P. Tan¹, G. Chaboussant³, F. Ott³, B. Warot-Fonrose², E. Snoeck², B. Chaudret¹, M. Respaud¹, K. Soulantica¹

¹Laboratoire de Physique et Chimie des Nano-objets (LPCNO), Toulouse

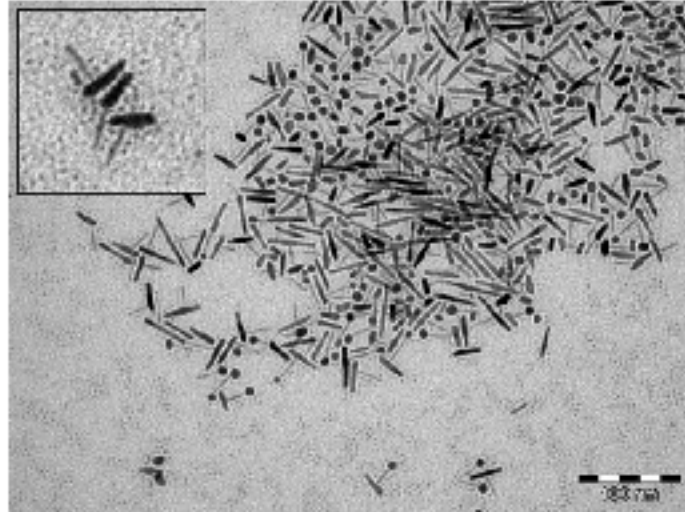
²CEMES-CNRS, Toulouse

³Laboratoire Léon Brillouin, Gif sur Yvette

TEM



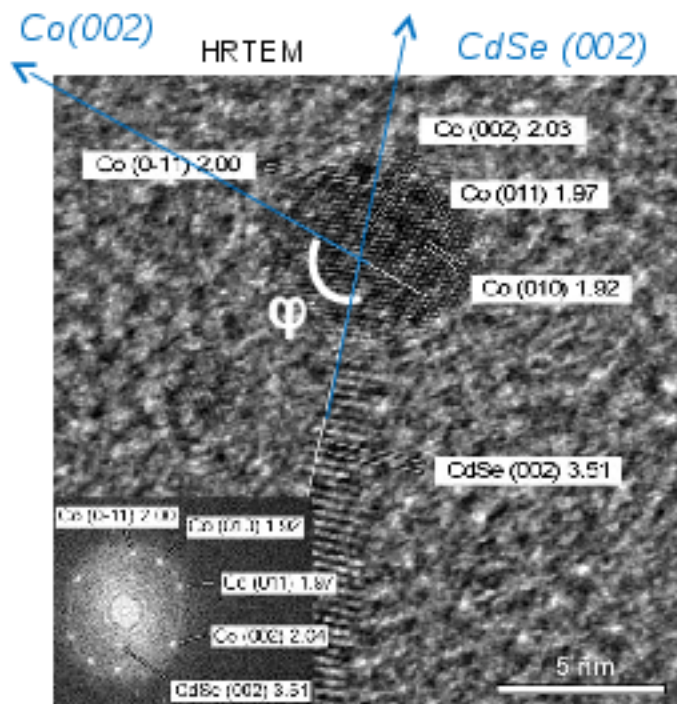
Conditions 1



Conditions 2

Sequential decomposition of organo-metallic precursors

- 1- decomposition of CdSe precursor and formation of the CdSe nanorods
- 2- decomposition of Co precursor: $[\text{Co}(\eta_4\text{-C}_8\text{H}_{12})(\eta_3\text{-C}_8\text{H}_{13})]$
- +HDA+LA under H_2 pressure for 24h

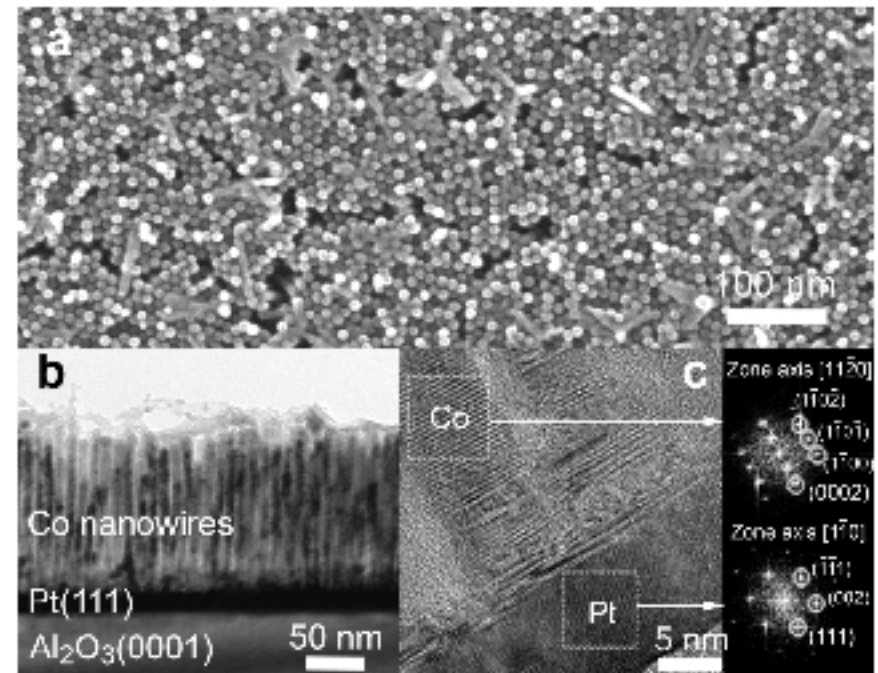
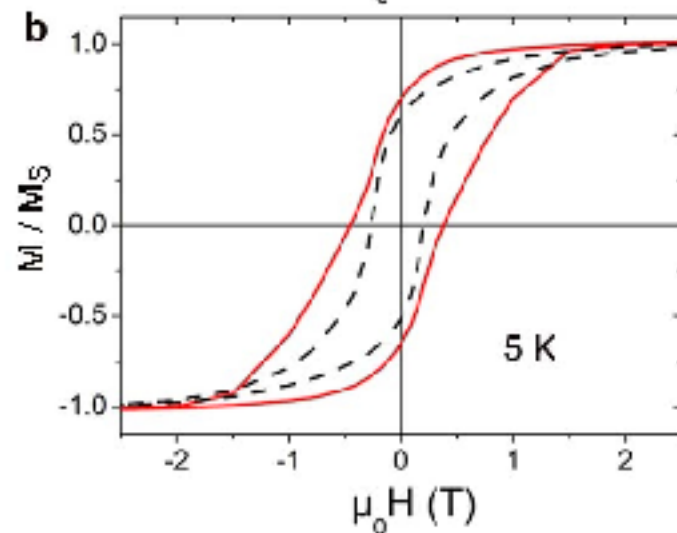
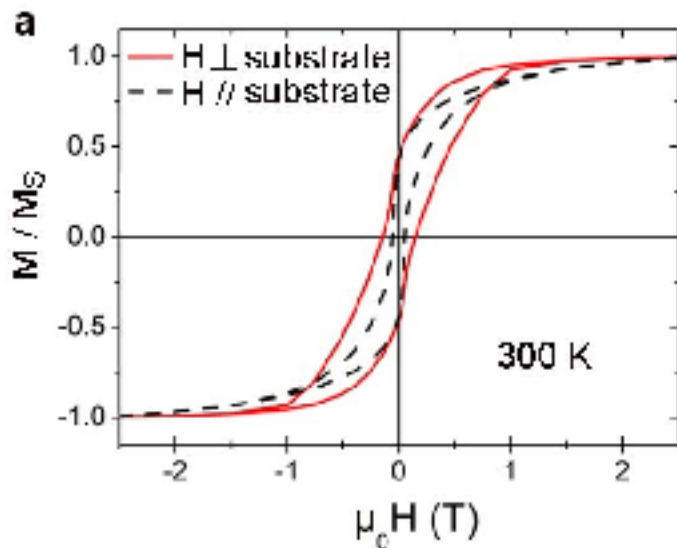


4 defined ϕ angles
between Co and CdSe
NRS

$112 \pm 3^\circ$, $135 \pm 3^\circ$
 $6 \pm 3^\circ$, $99 \pm 3^\circ$

Epitaxial growth of Co on nano-objects

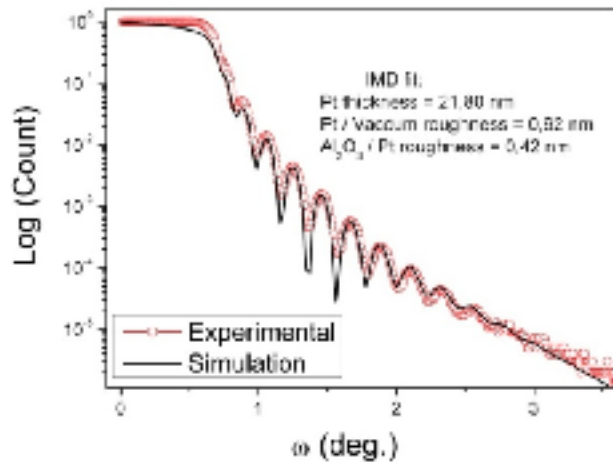
Magnetic properties of the 7 T-wire/in² array (SQUID)



300K: $\mu_0 H_{c^{\perp}} = 147$ mT ; $M_r/M_s^{\perp} = 0.46$
 $\mu_0 H_{c^{\parallel}} = 57$ mT ; $M_r/M_s^{\parallel} = 0.43$

5K: $\mu_0 H_{c^{\perp}} = 417$ mT ; $M_r/M_s^{\perp} = 0.7$; $\mu_0 H_{EB} = -35$ mT
 $\mu_0 H_{c^{\parallel}} = 234$ mT ; $M_r/M_s^{\parallel} = 0.6$; $\mu_0 H_{EB} = -35$ mT

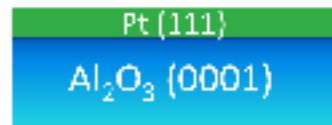
X-ray reflectivity (XRR)



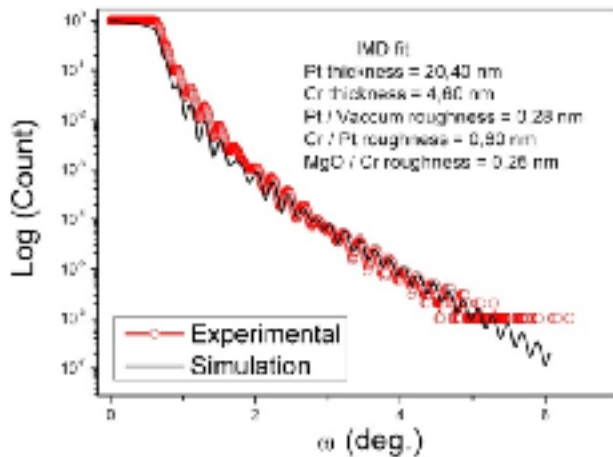
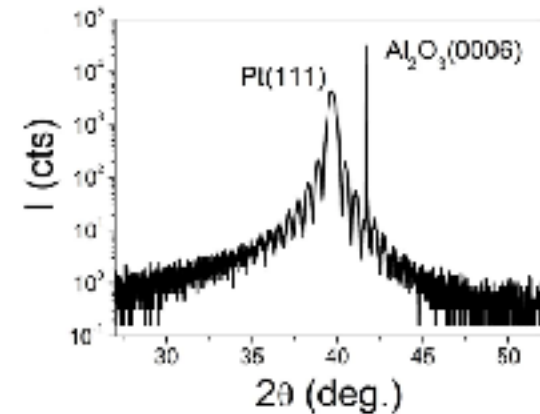
Pt (111) (20 nm) / Al₂O₃ (0001)

Al₂O₃: recuit à 750°C / 30 min
 Pt: 500°C (2.90 nm/min)

1*1 cm²



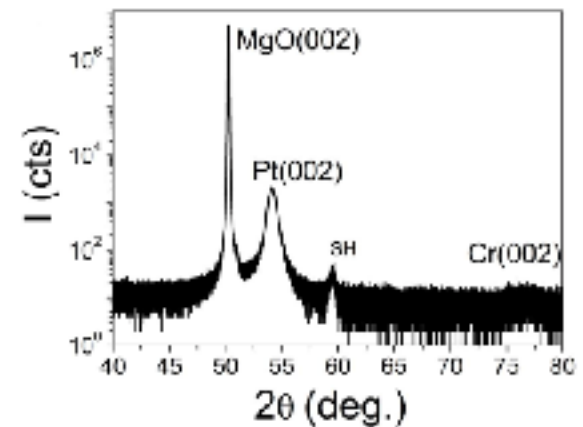
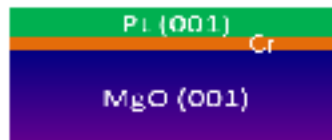
X-ray diffraction (XRD)



Pt (001) (20nm) / Cr (5nm) / MgO (001)

MgO: recuit à 750°C / 30 min
 Cr: évaporée à 360°C (0.15 nm/sec)
 Pt: 360°C (2.90 nm/min)

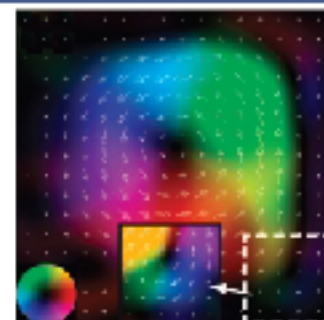
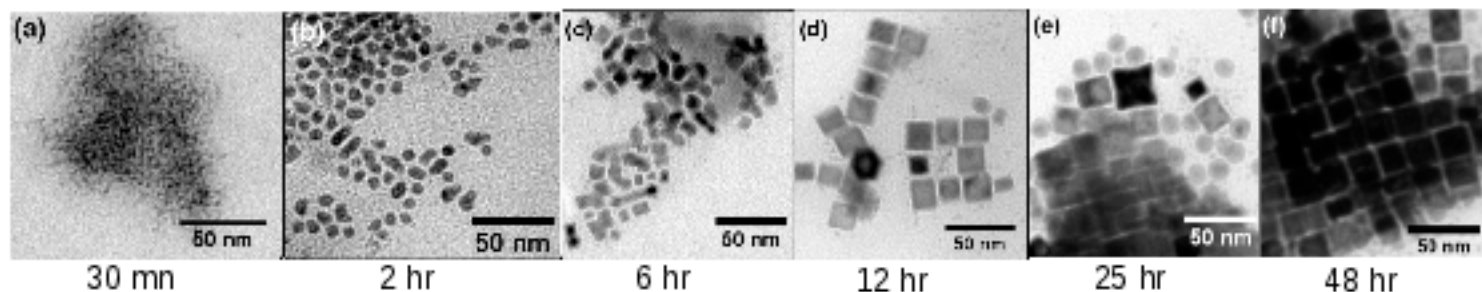
1*1 cm²



Iron Nanoparticles on Pt films

Homogeneous nucleation

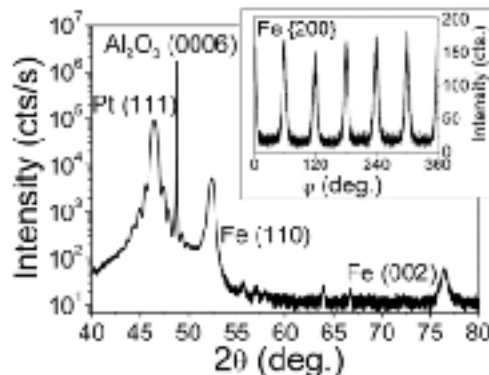
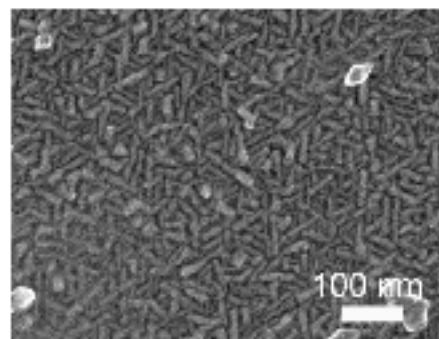
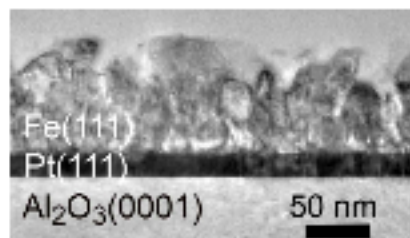
$\{\text{Fe}[\text{N}(\text{SiMe}_3)_2]_2\} + \text{HDA} + \text{PA}$ (Palmitic Acid $\text{CH}_3(\text{CH}_2)_{14}\text{COOH}$)



Induction mapping

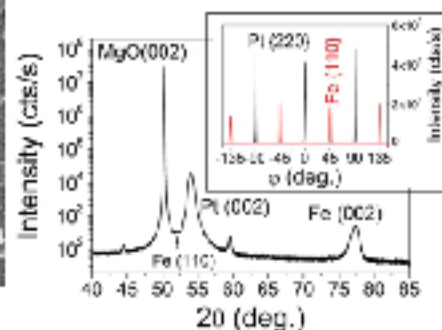
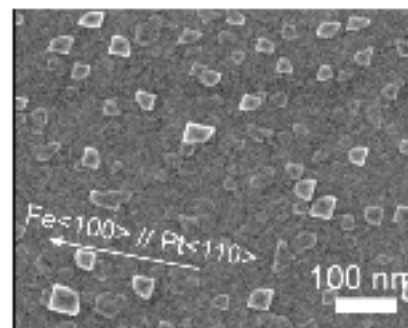
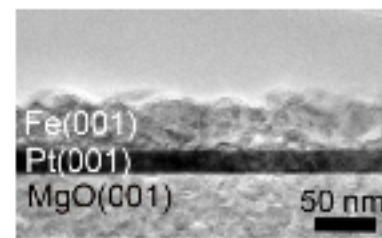
Fe / Pt (111) 20nm / Al_2O_3 (0001)

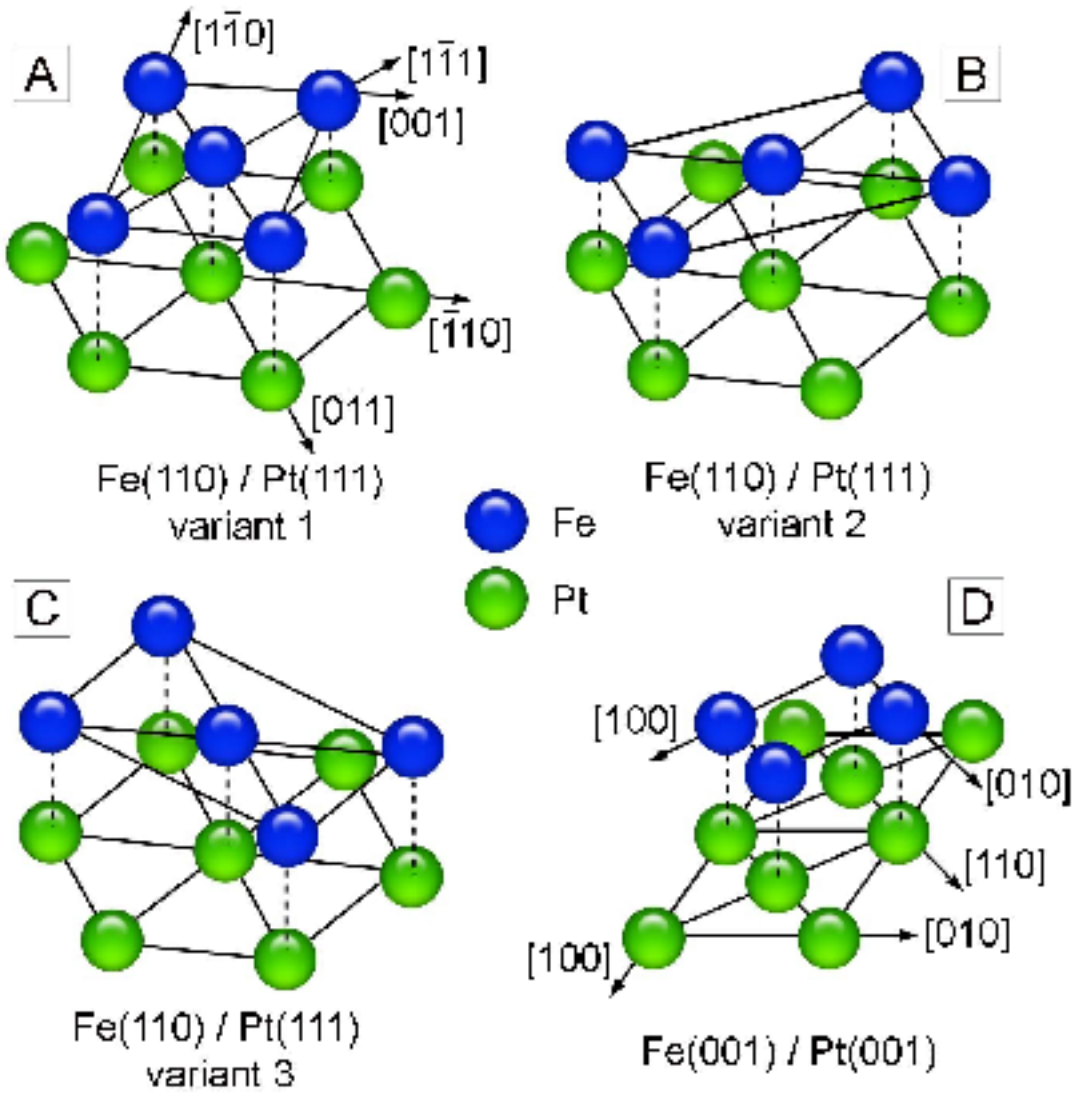
Epitaxial growth
Fe (110) // Pt (111)



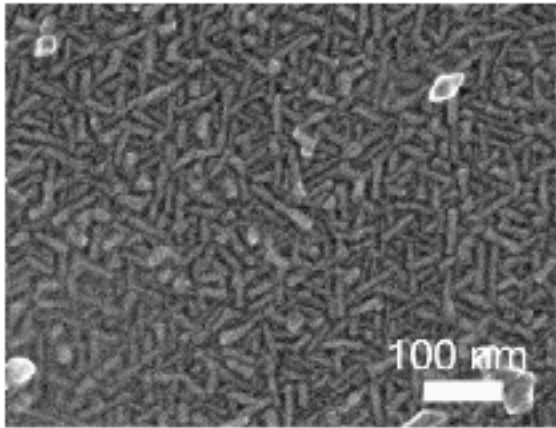
Fe / Pt(001) 20nm / MgO(001)

Epitaxial growth
Fe (001)[110] // Pt (001)[010]

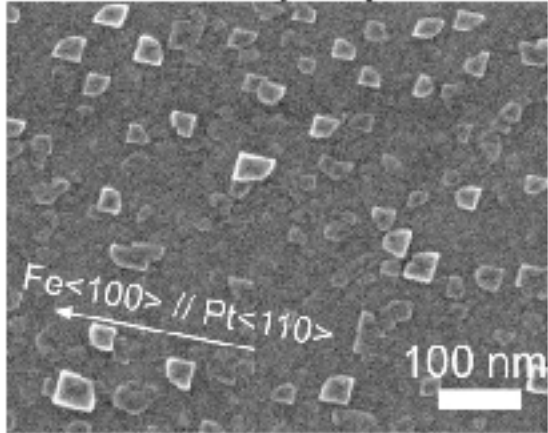


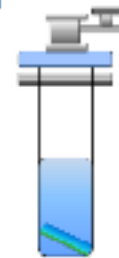


Fe / Pt(111)



Fe / Pt(001)

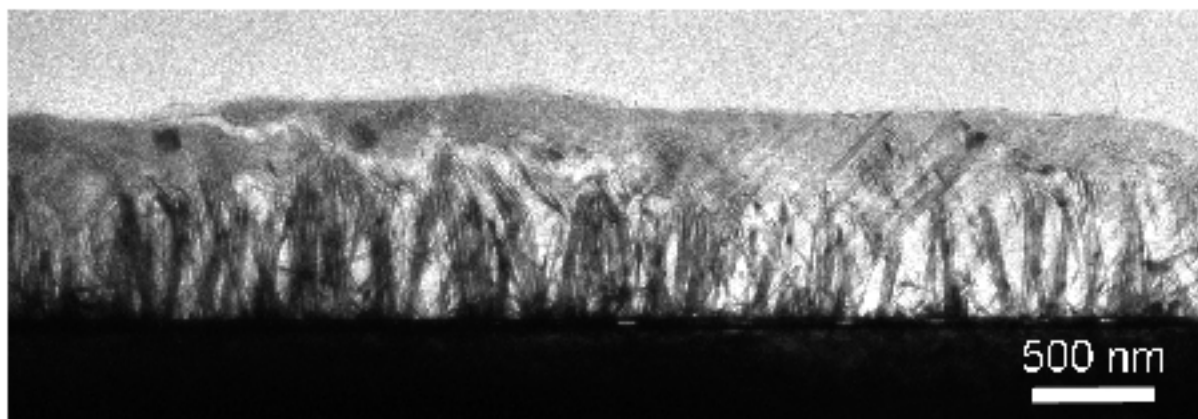
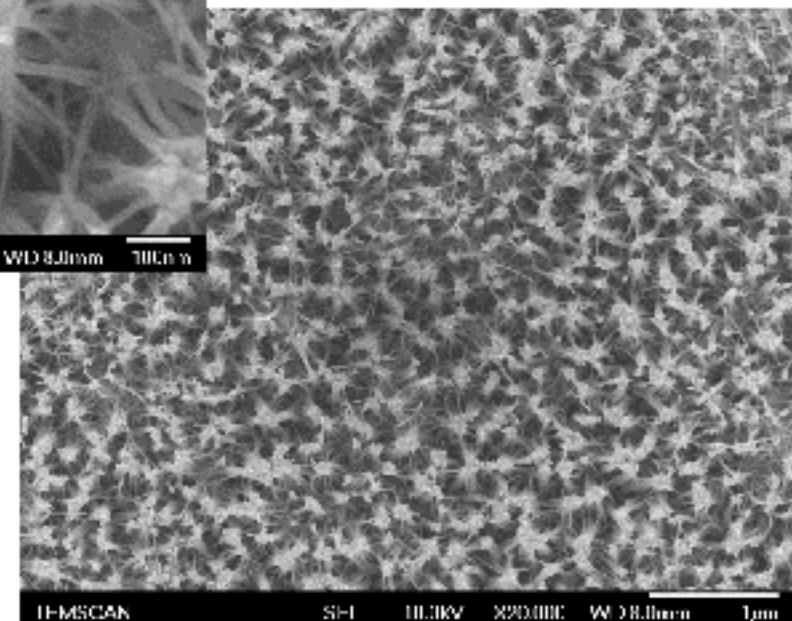
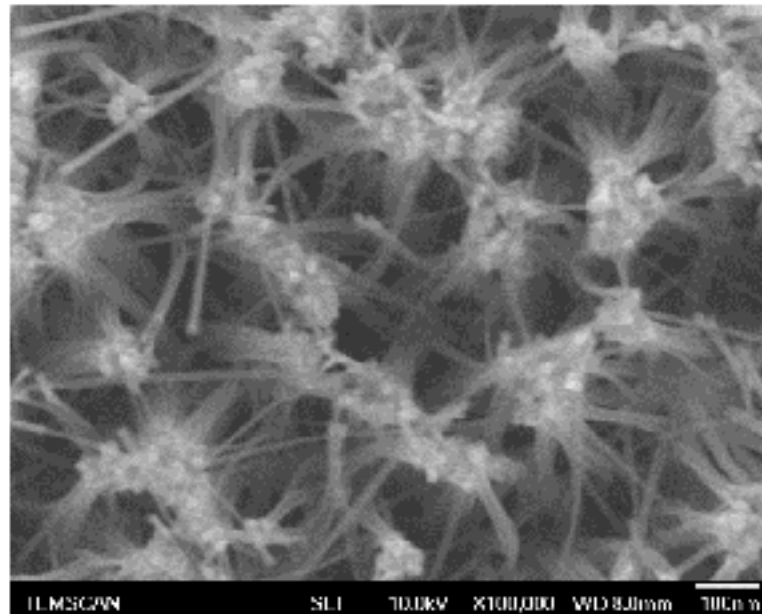
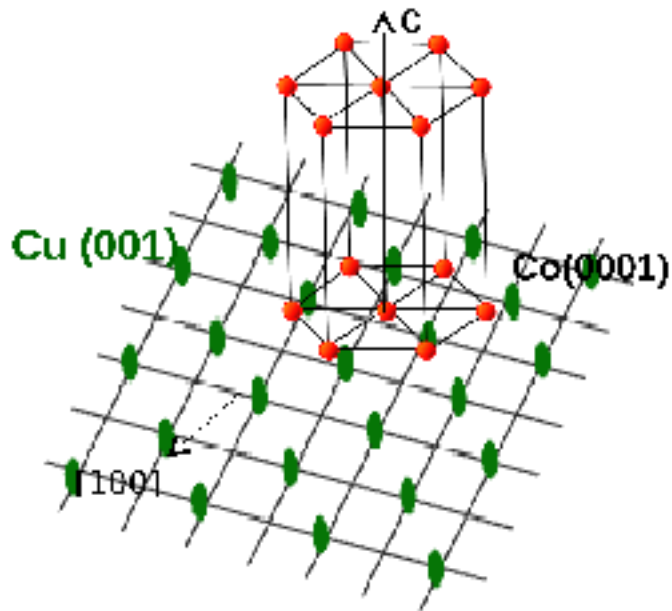




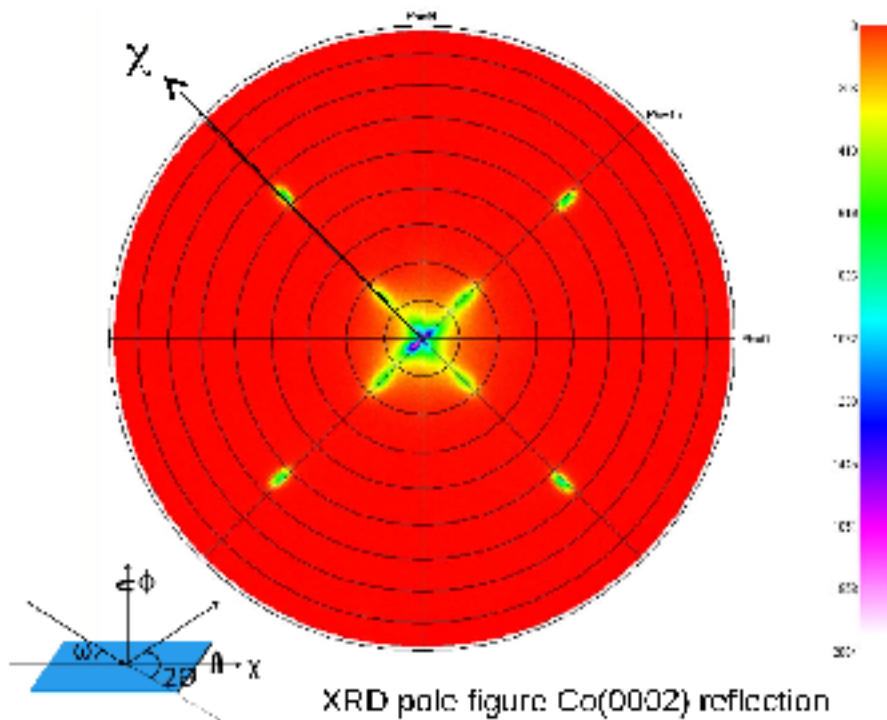
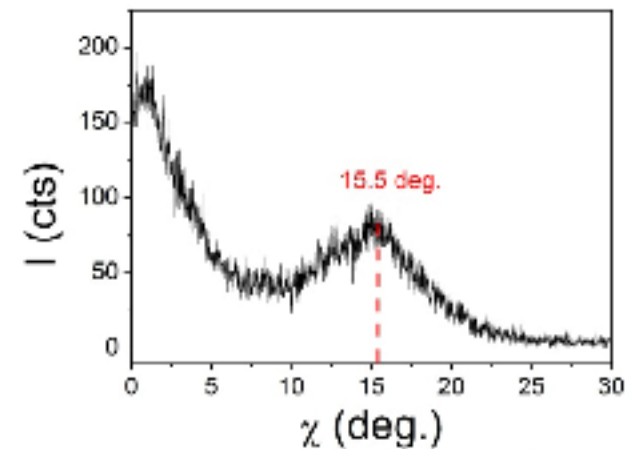
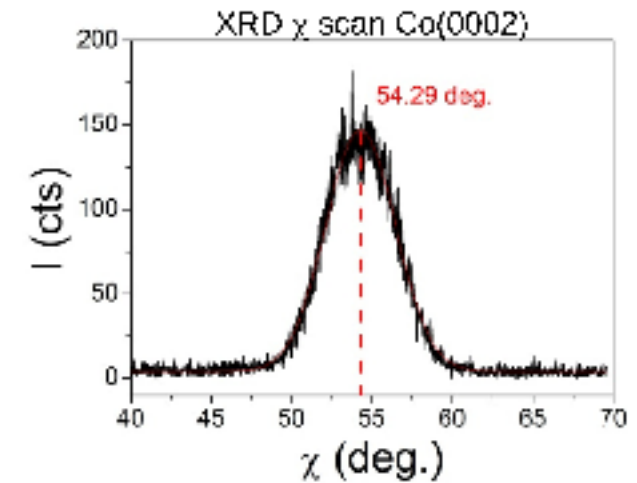
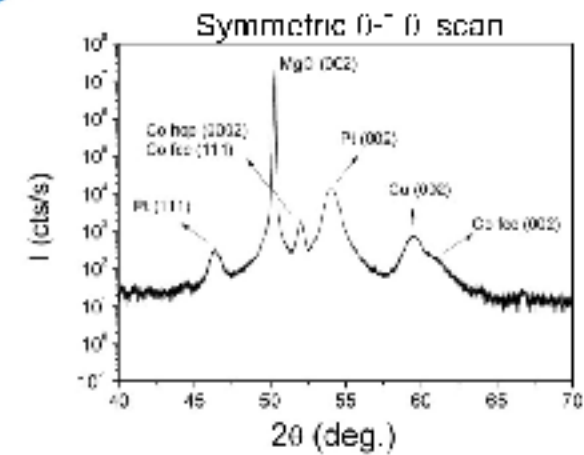
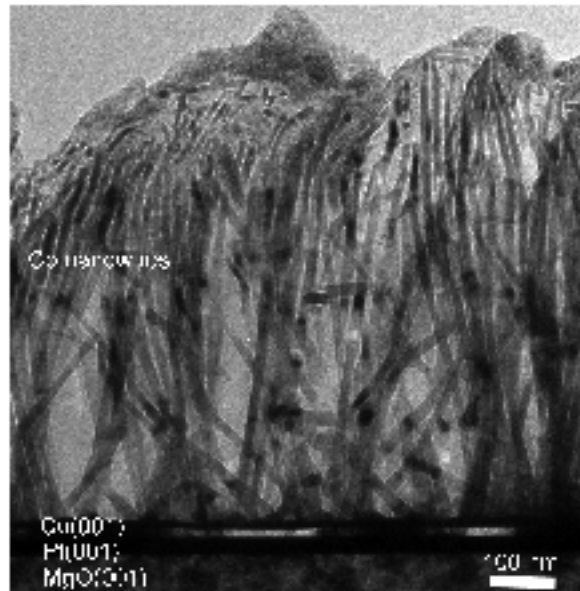
Sputtering deposition:
Cu 20nm 300°C / Pt 20nm 350 °C / Cr
5nm 360°C / MgO(001)

1

2

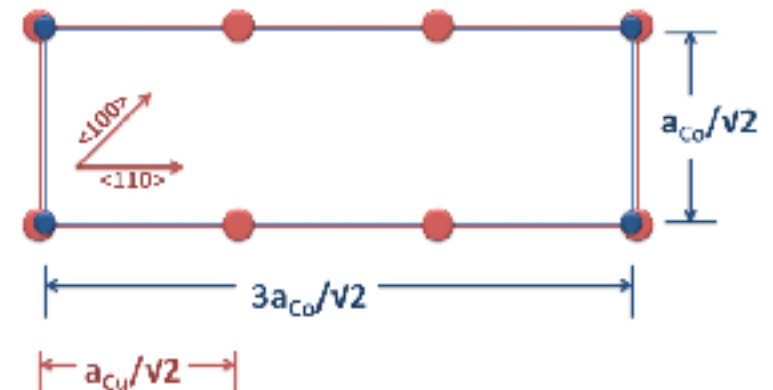
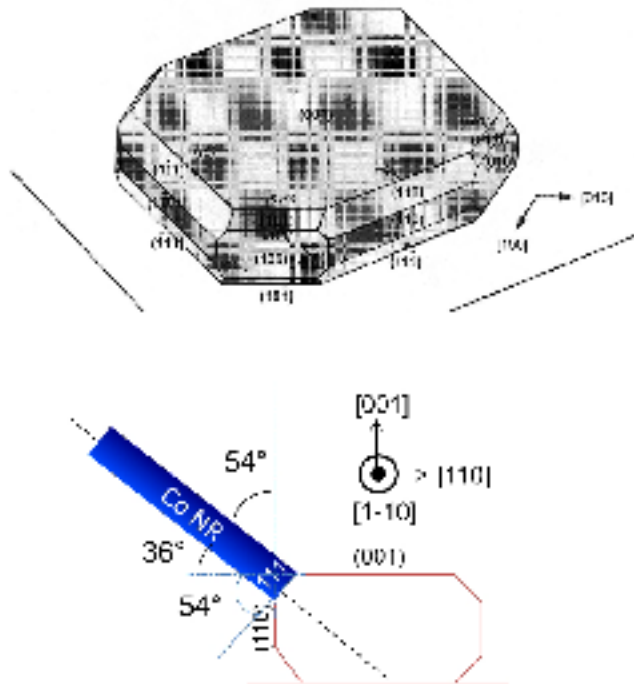


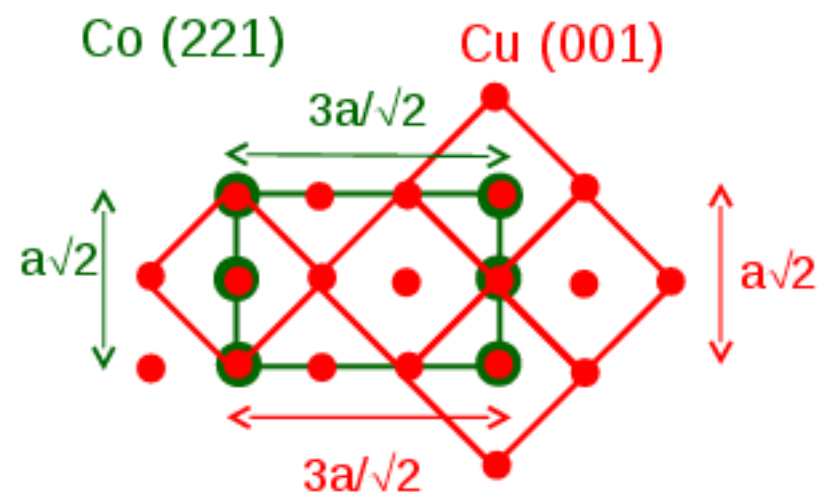
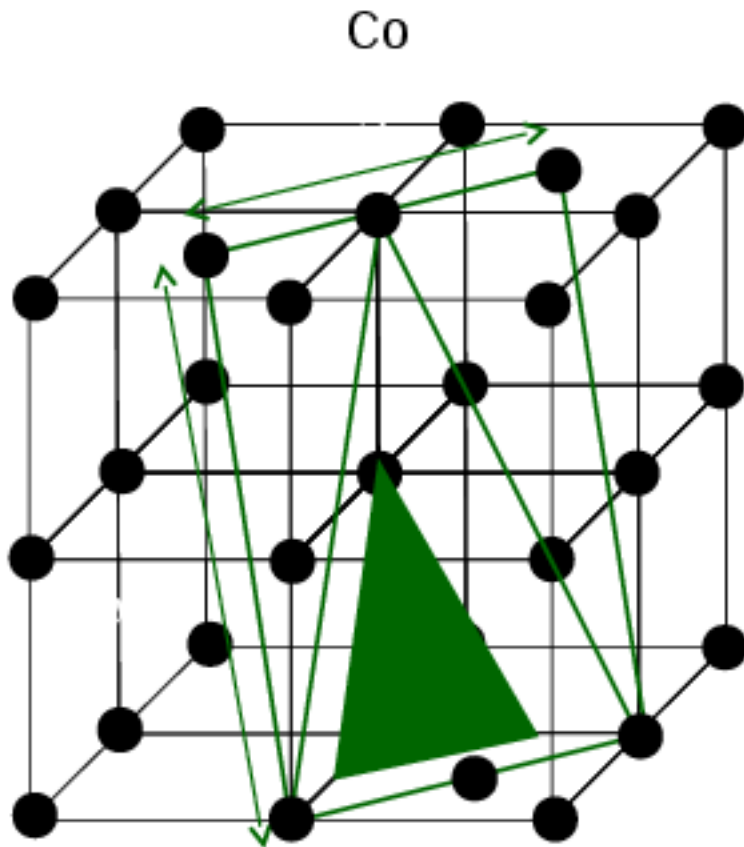
Influence of the film surface symmetry Co NW / Cu(001)



Hypothesis: 3D growth of Co / Cu(001)

Co NW grown at 15° from the substrate normal





Misfit Co/Cu: - 1.93%